SYLLABUS (BT-201)

ENGINEERING PHYSICS

UNIT 1:

Module 1: Wave nature of particles and the Schrodinger equation (8 lectures) Introduction to Quantum mechanics, Wave nature of Particles, operators, Time-dependent and timeindependent Schrodinger equation for wavefunction, Application: Particle in a One dimensional Box, Born interpretation, Free-particle wavefunction and wave-packets, vg and vp relation Uncertainty principle.

UNIT 2:

Module 2: Wave optics (8 lectures) Huygens' principle, superposition of waves and interference of light by wave front splitting and amplitude splitting; Young's double slit experiment, Newton's rings, Michelson interferometer, MachZehnder interferometer.

Farunhofer diffraction from a single slit and a circular aperture, the Rayleigh criterion for limit of resolution and its application to vision; Diffraction gratings and their resolving power.

UNIT 3:

Module 3: Introduction to solids (8 lectures) Free electron theory of metals, Fermi level of Intrinsic and extrinsic, density of states, Bloch's theorem for particles in a periodic potential, Kronig-Penney model(no derivation) and origin of energy bands. V-I characteristics of PN junction, Zener diode, Solar Cell, Hall Effec.

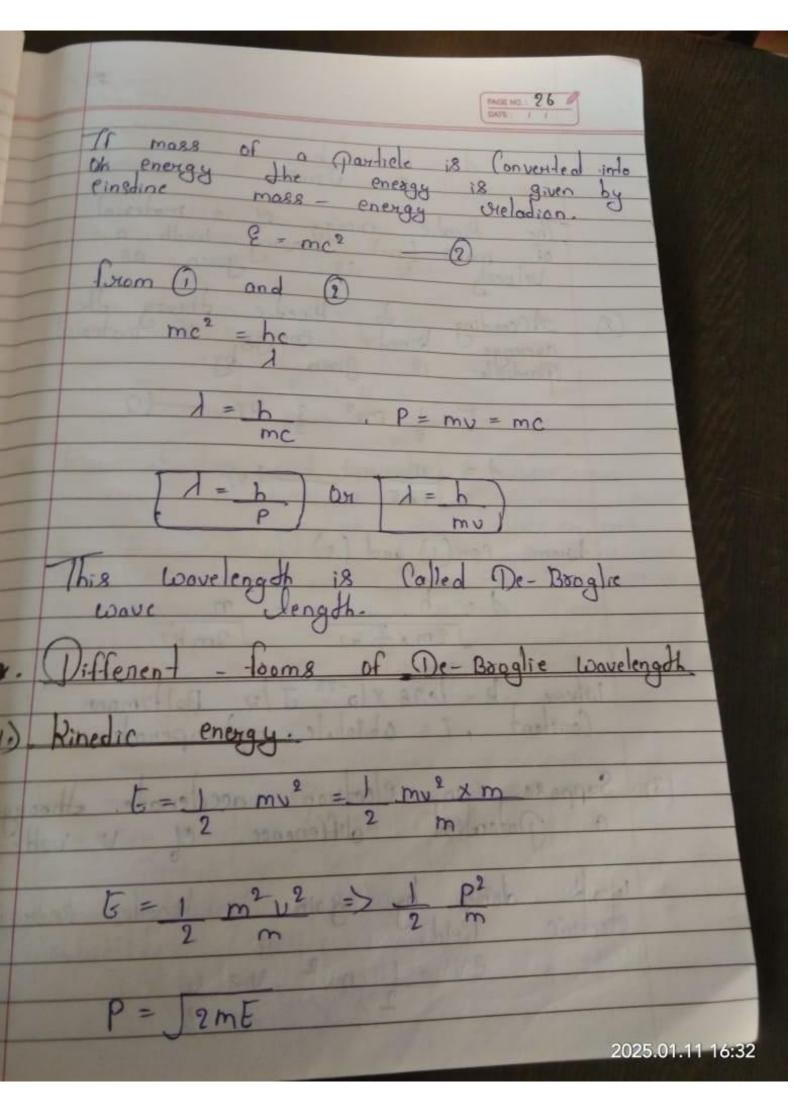
UNIT 4:

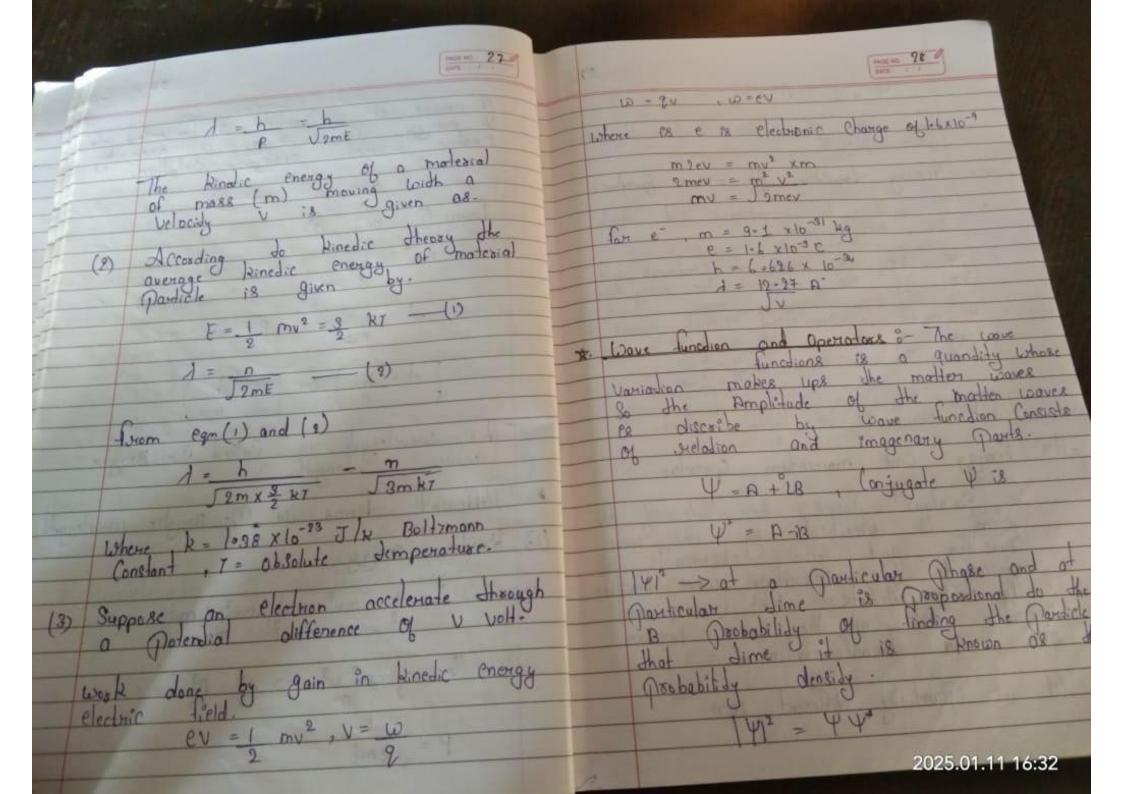
Module 4: Lasers (8 lectures) Einstein's theory of matter radiation interaction and A and B coefficients; amplification of light by population inversion, different types of lasers: gas lasers (He-Ne, CO2), solid-state lasers(ruby, Neodymium), Properties of laser beams: mono-chromaticity, coherence, directionality and brightness, laser speckles, applications of lasers in science, engineering and medicine. Introduction to Optical fiber, acceptance angle and cone, Numerical aperture, V number, attenuation.

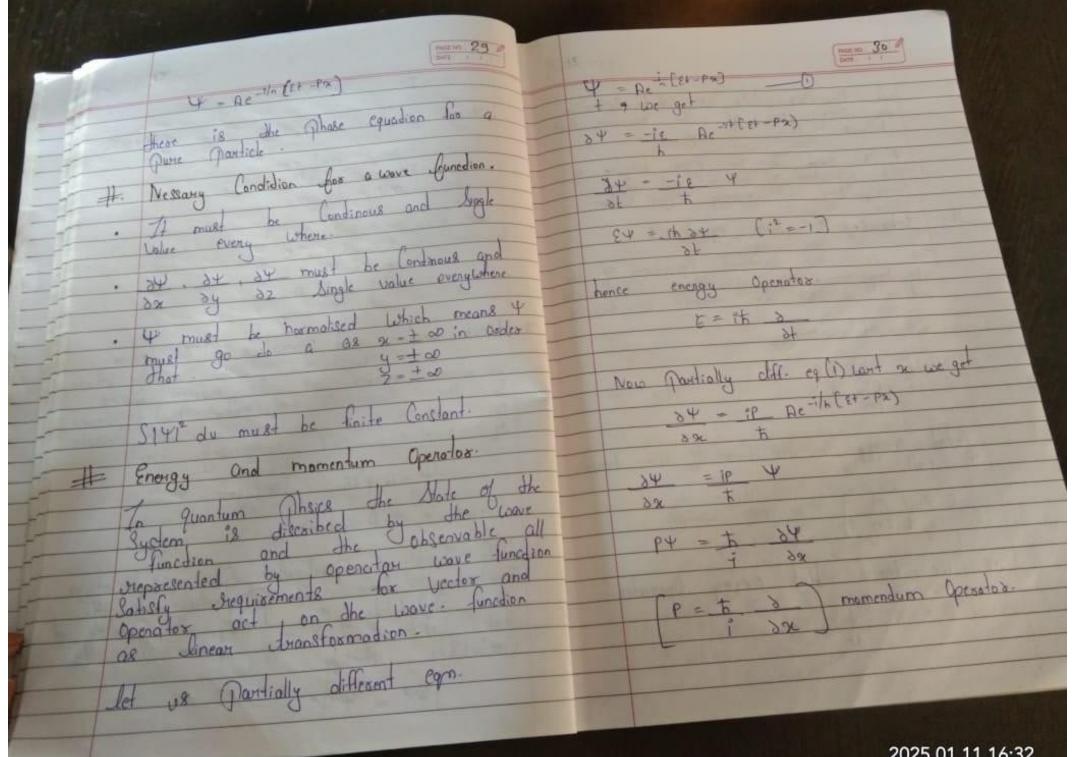
UNIT 5:

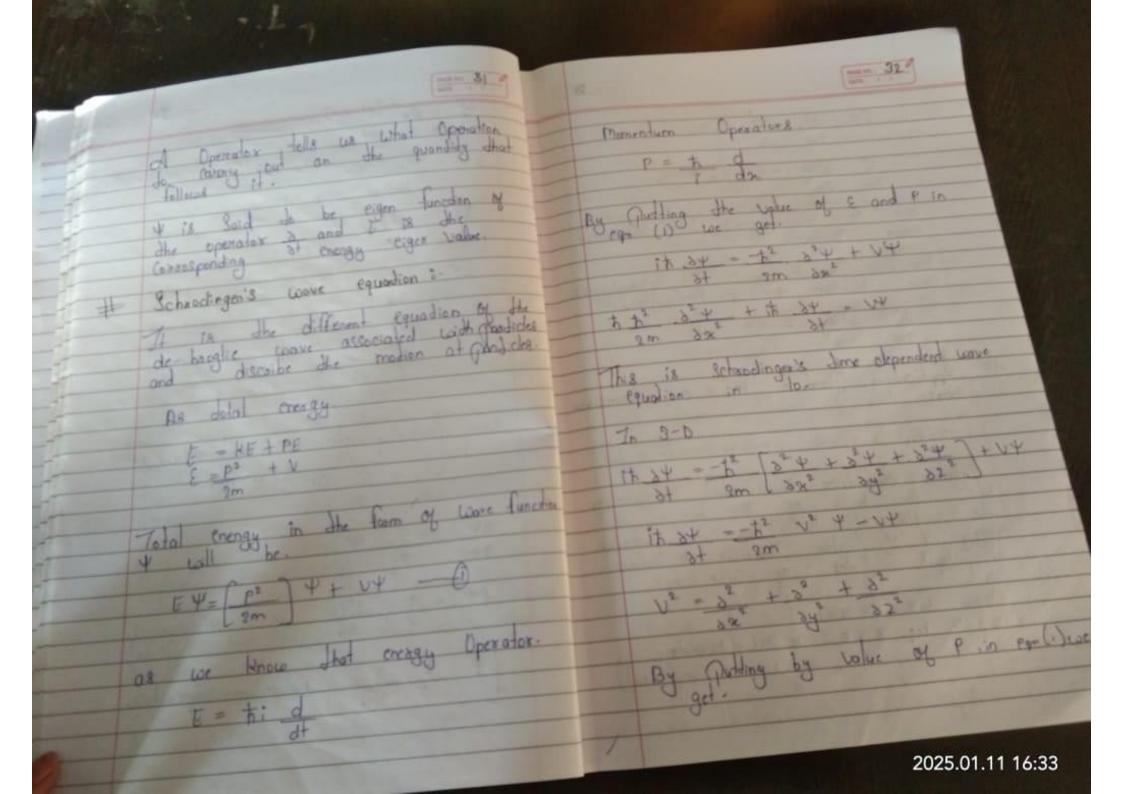
Module 5: Electrostatics in vacuum (8 lectures) Calculation of electric field and electrostatic potential for a charge distribution; Electric displacement, Basic Introduction to Dielectrics, Gradient, Divergence and curl, Stokes' theorem, Gauss Theorem, Continuity equation for current densities; Maxwell's equation in vacuum and non-conducting medium; Poynting vector.

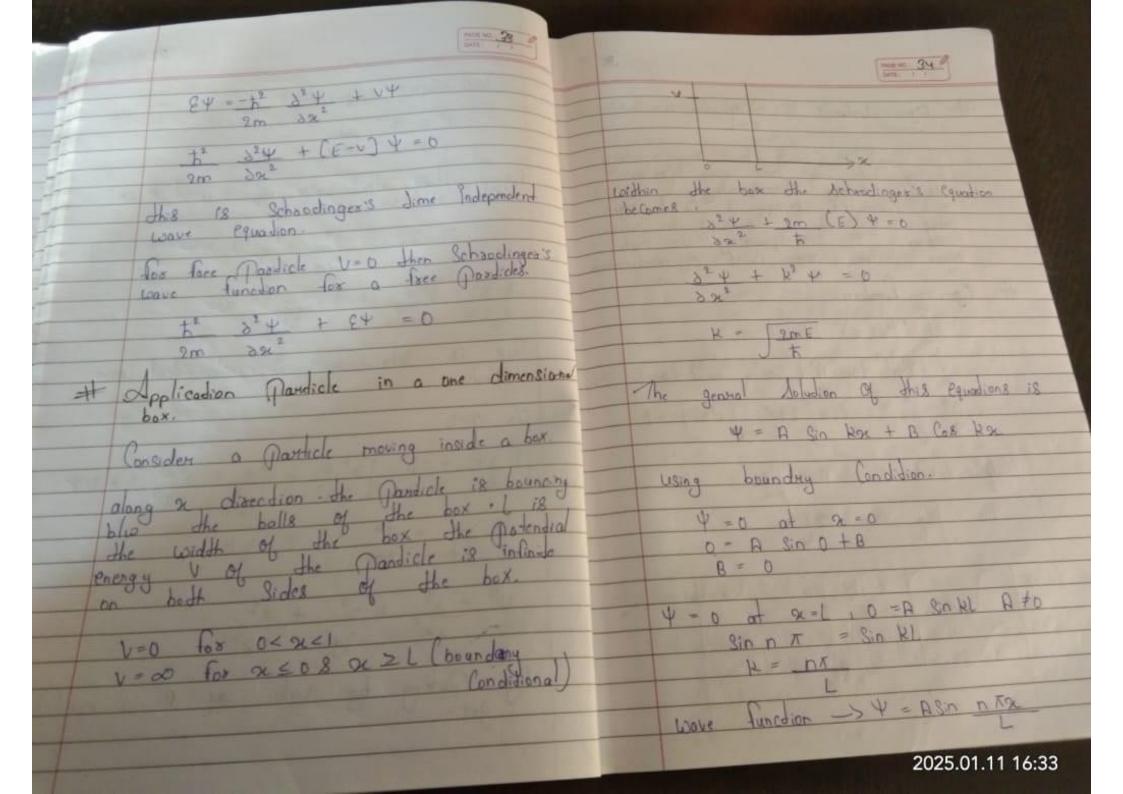
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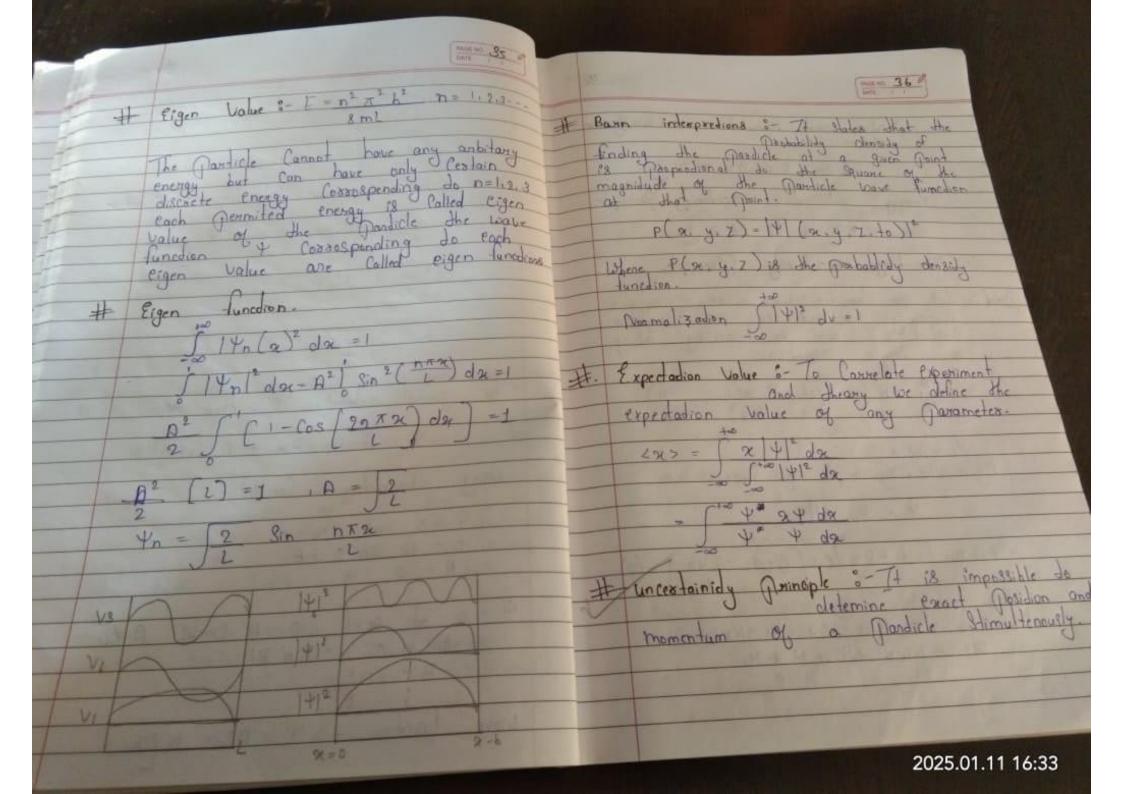


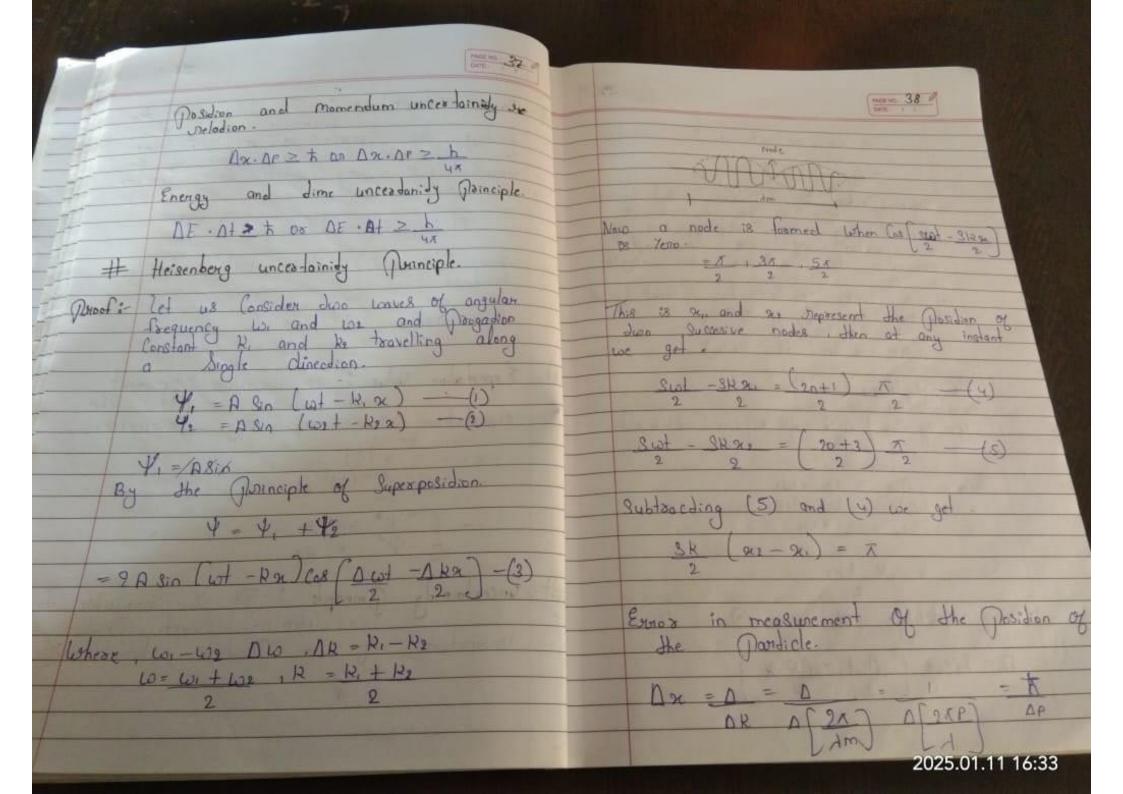


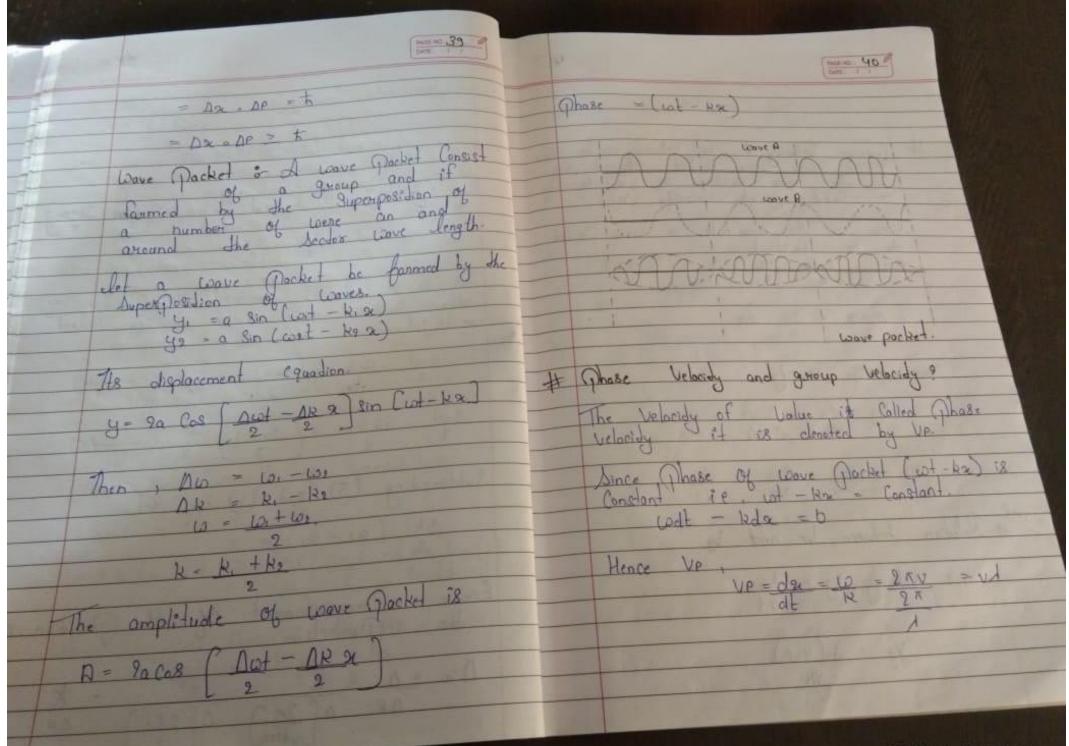


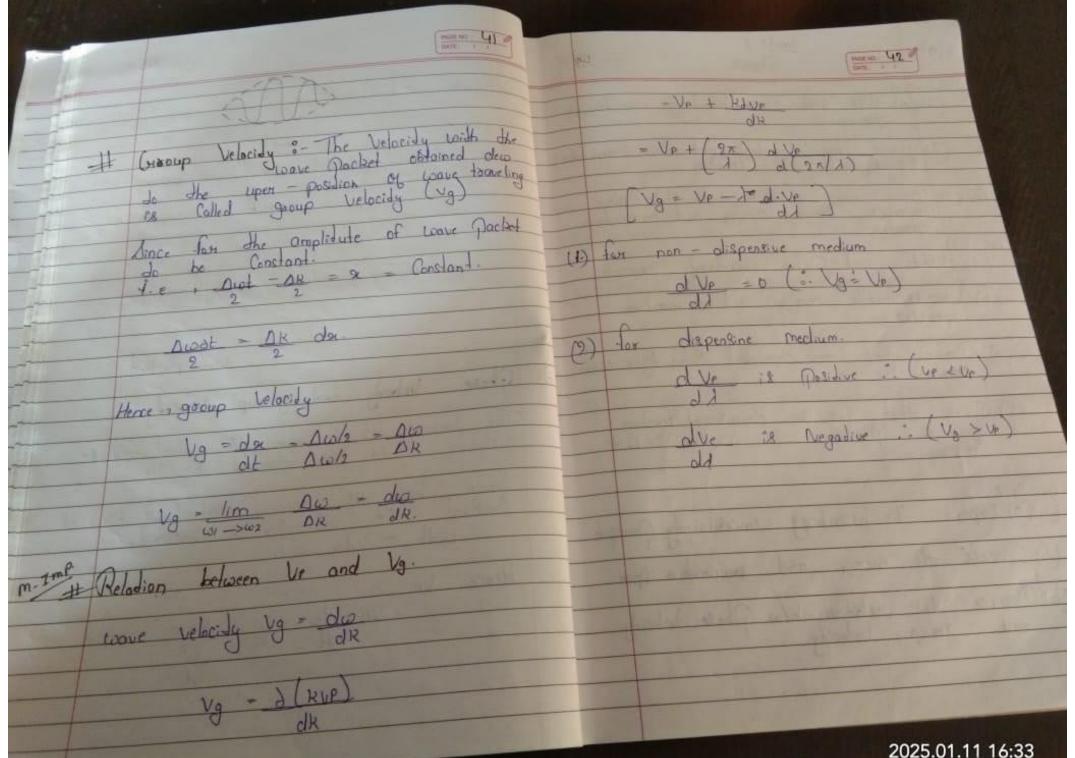


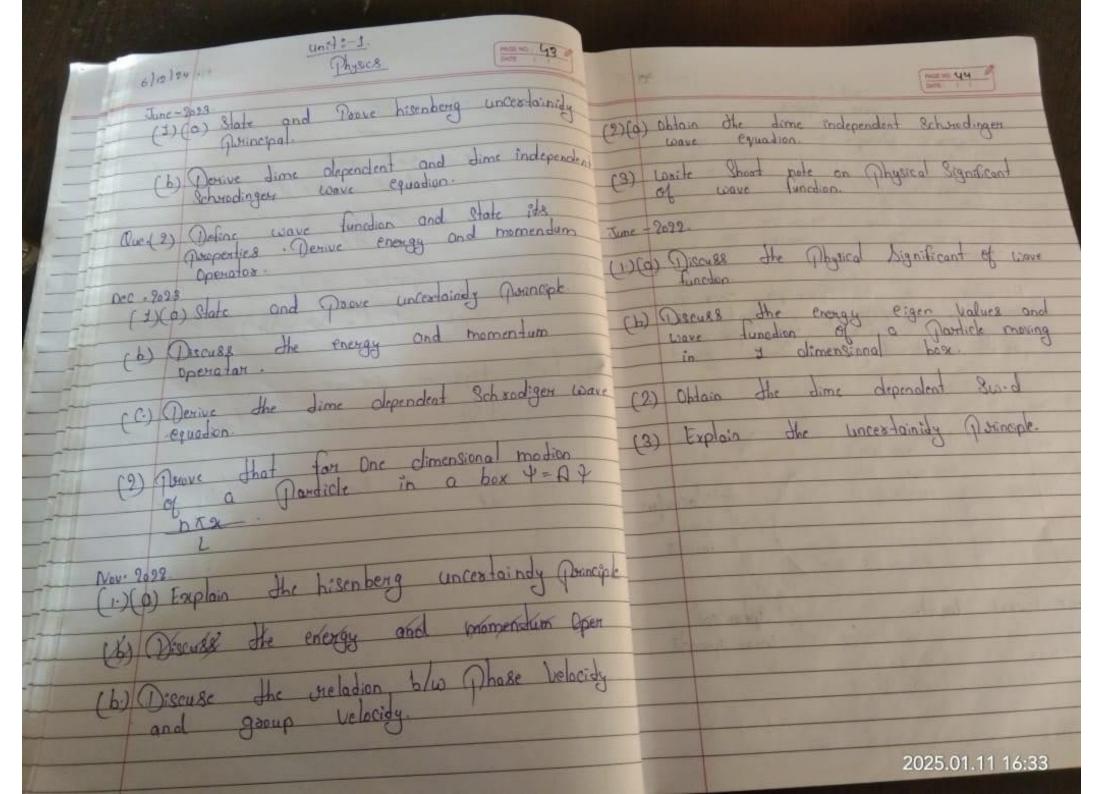


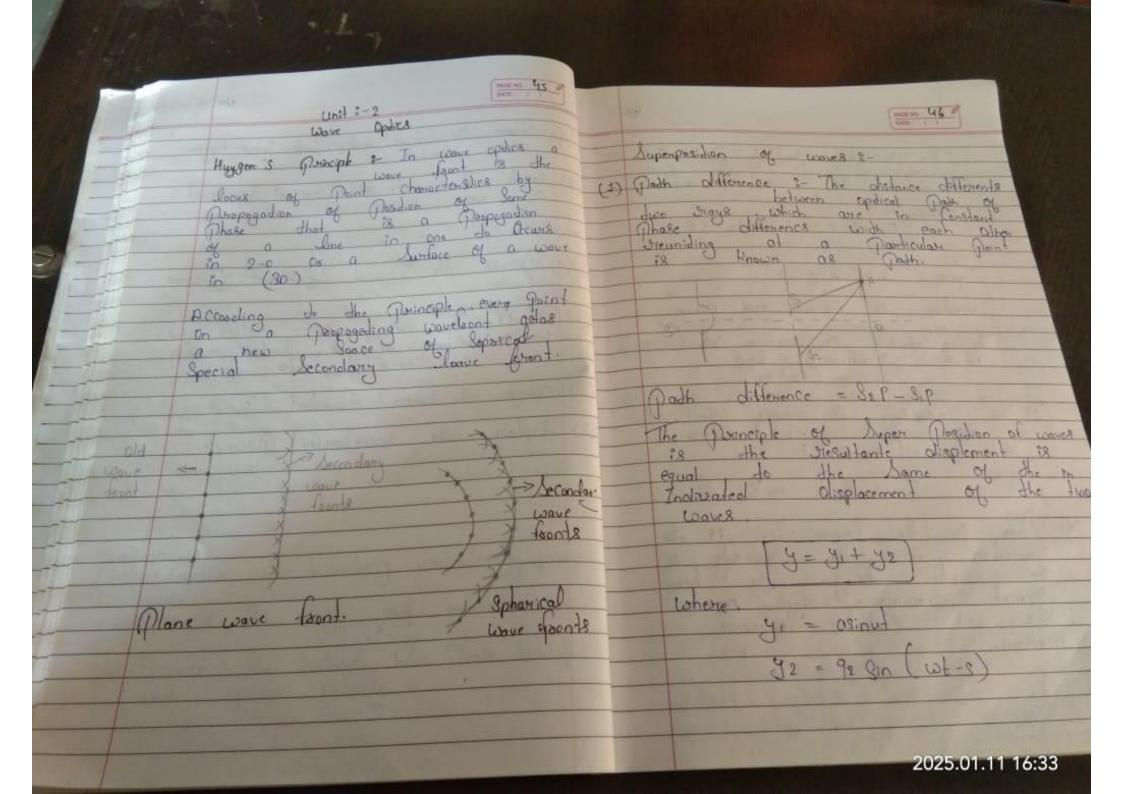


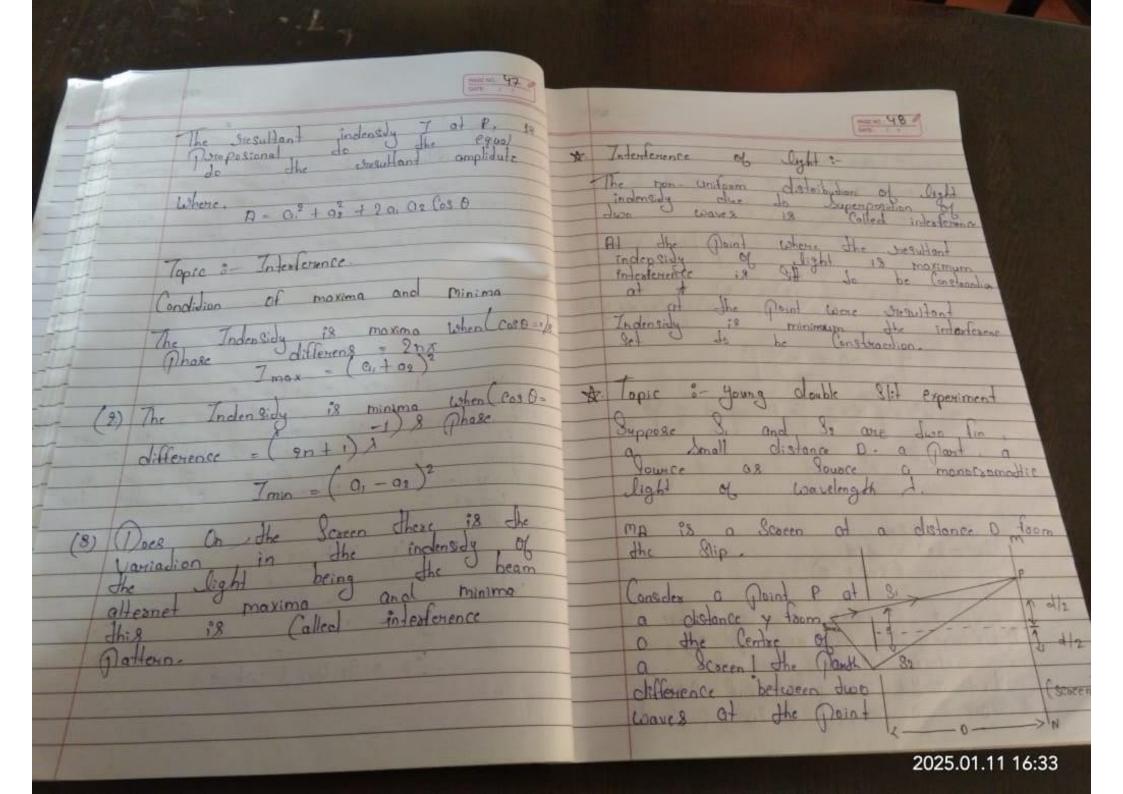


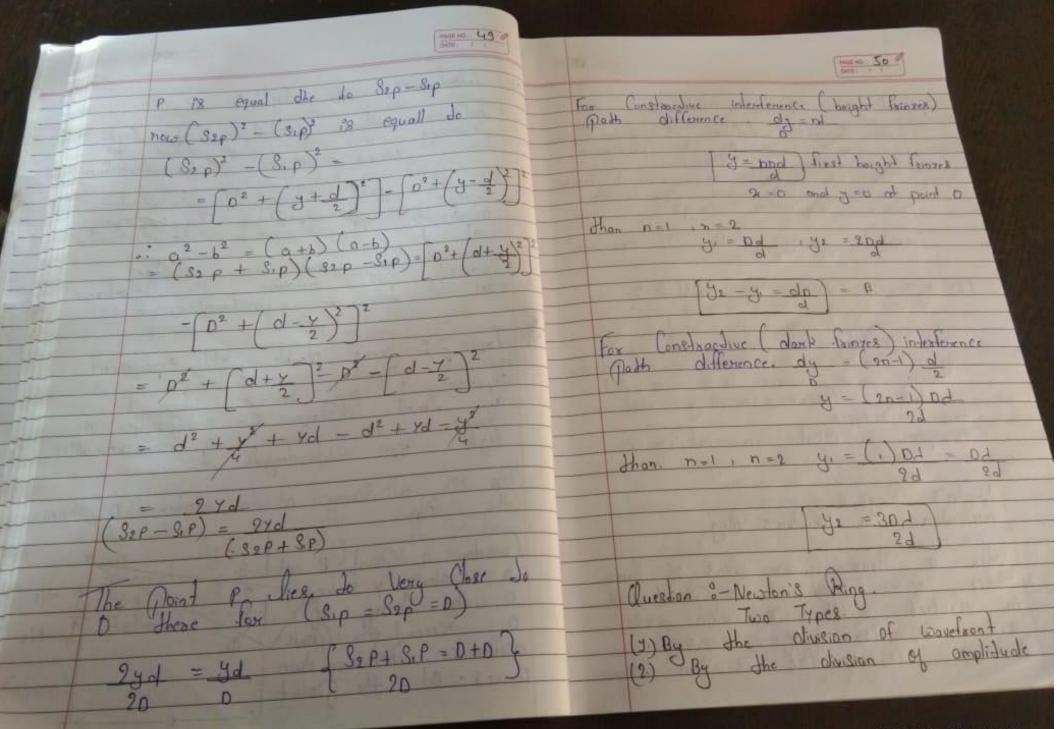


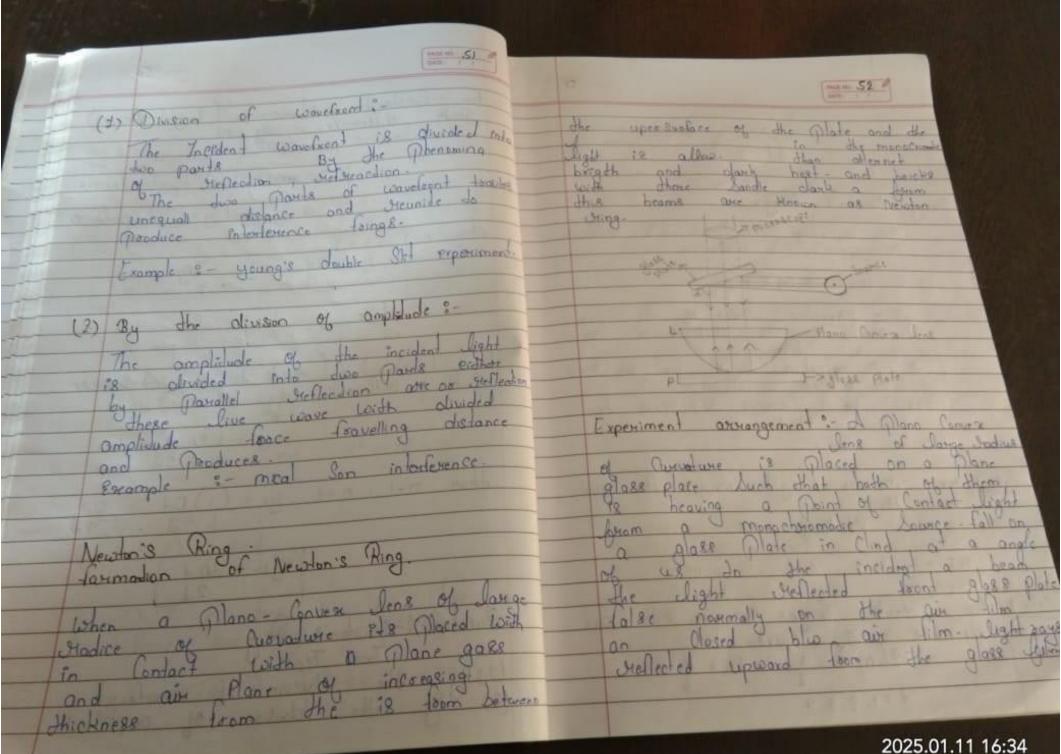


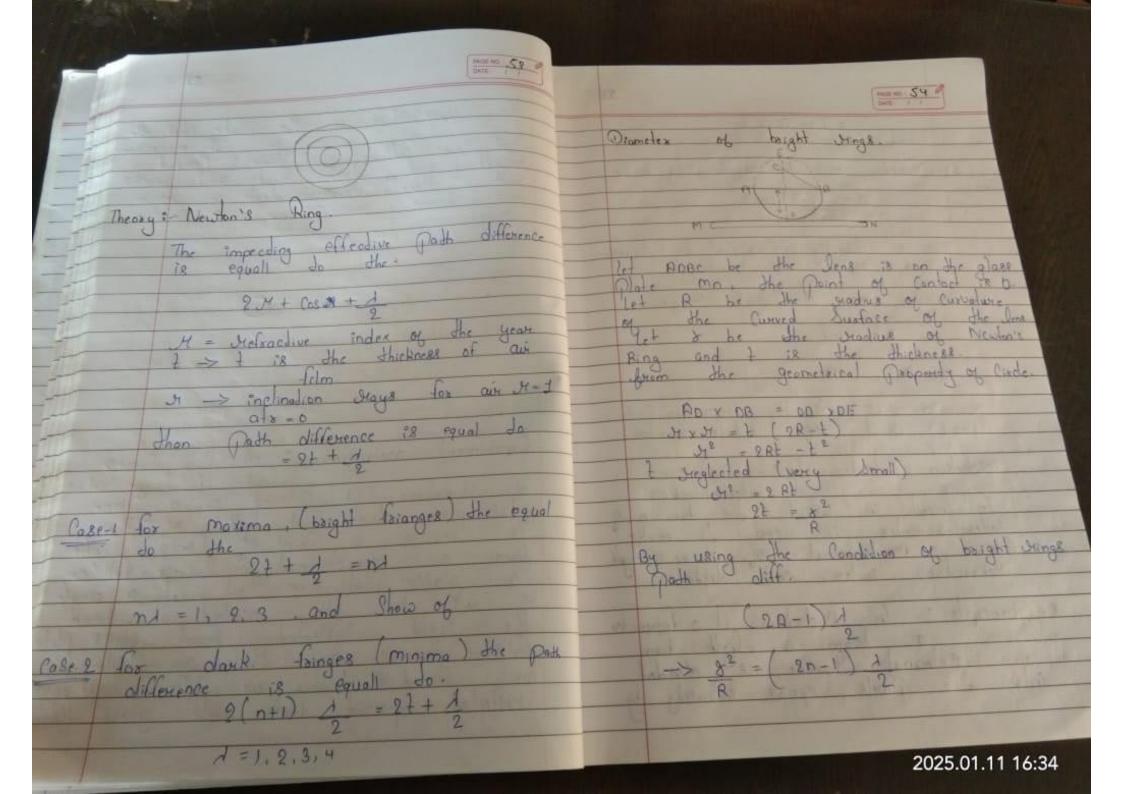


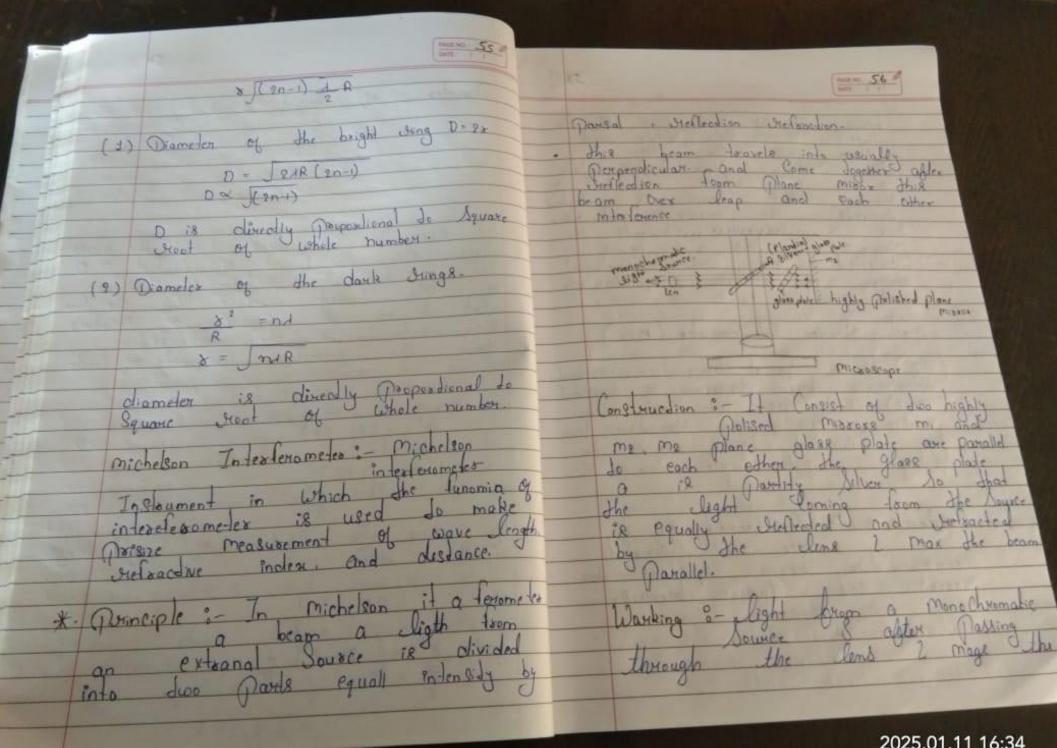


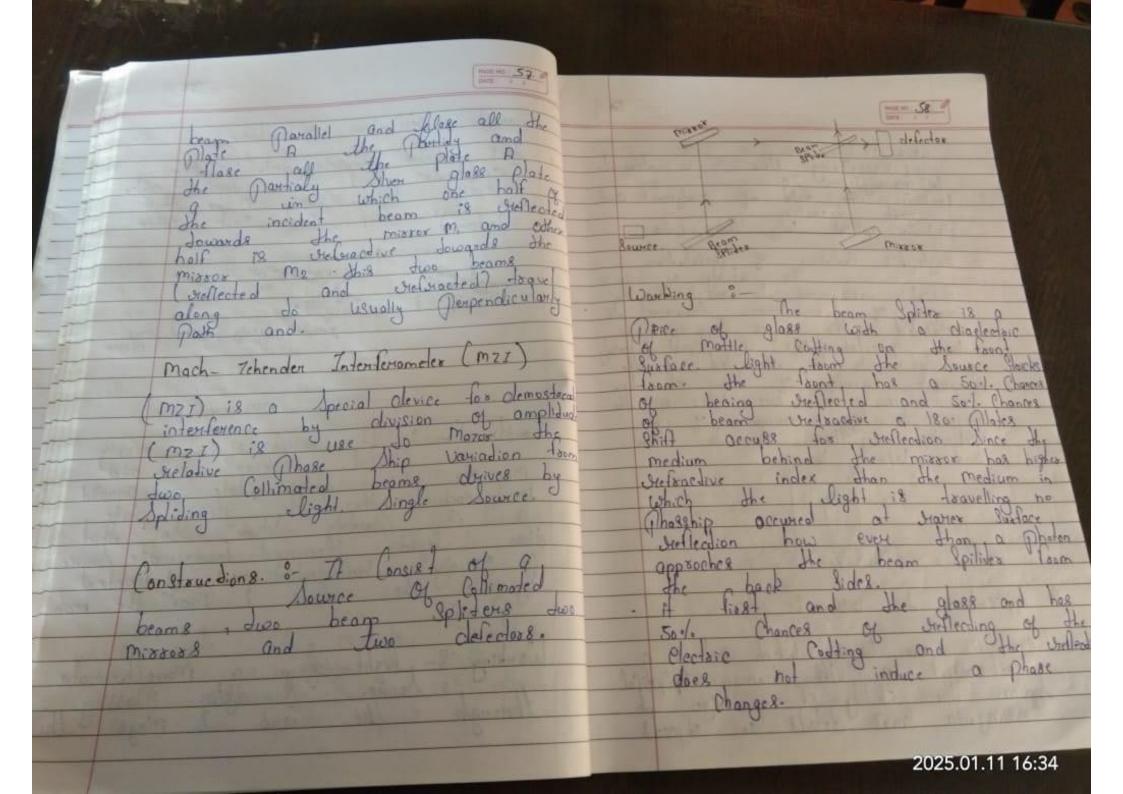


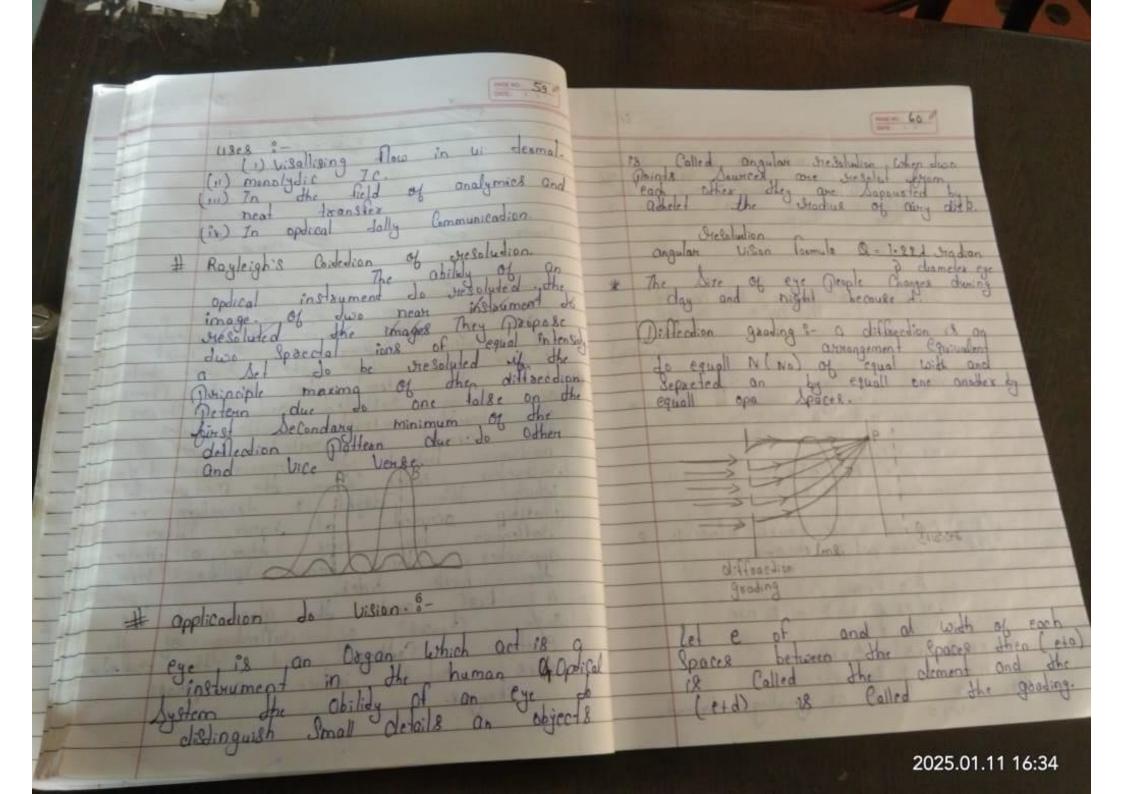


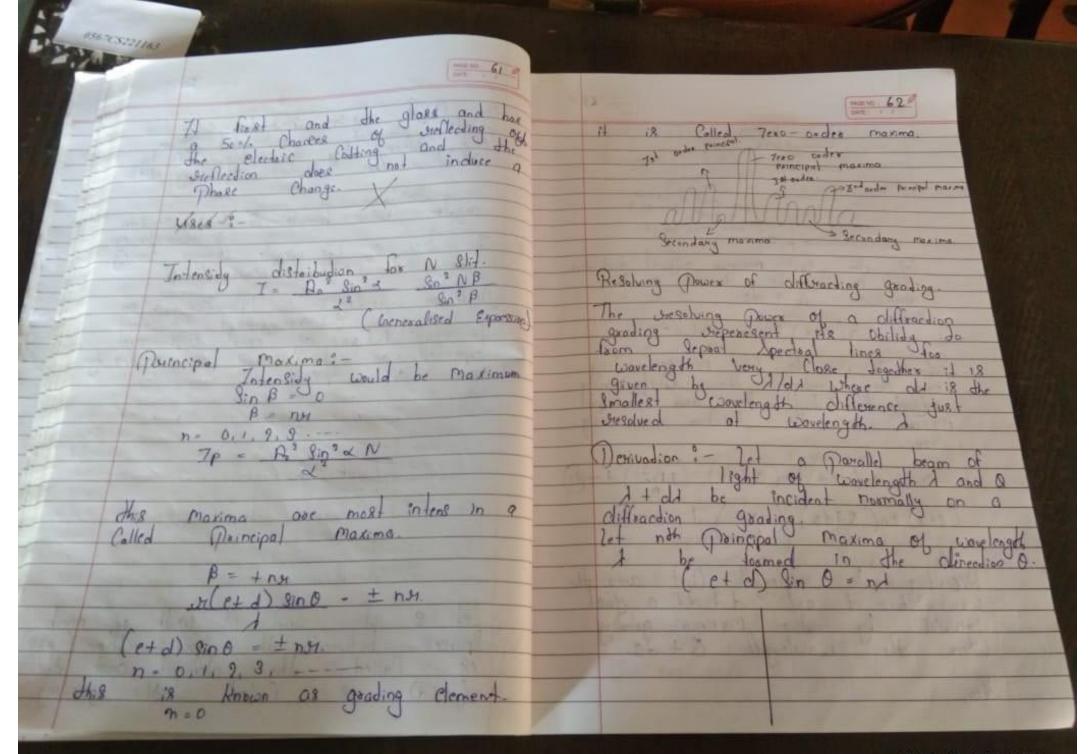


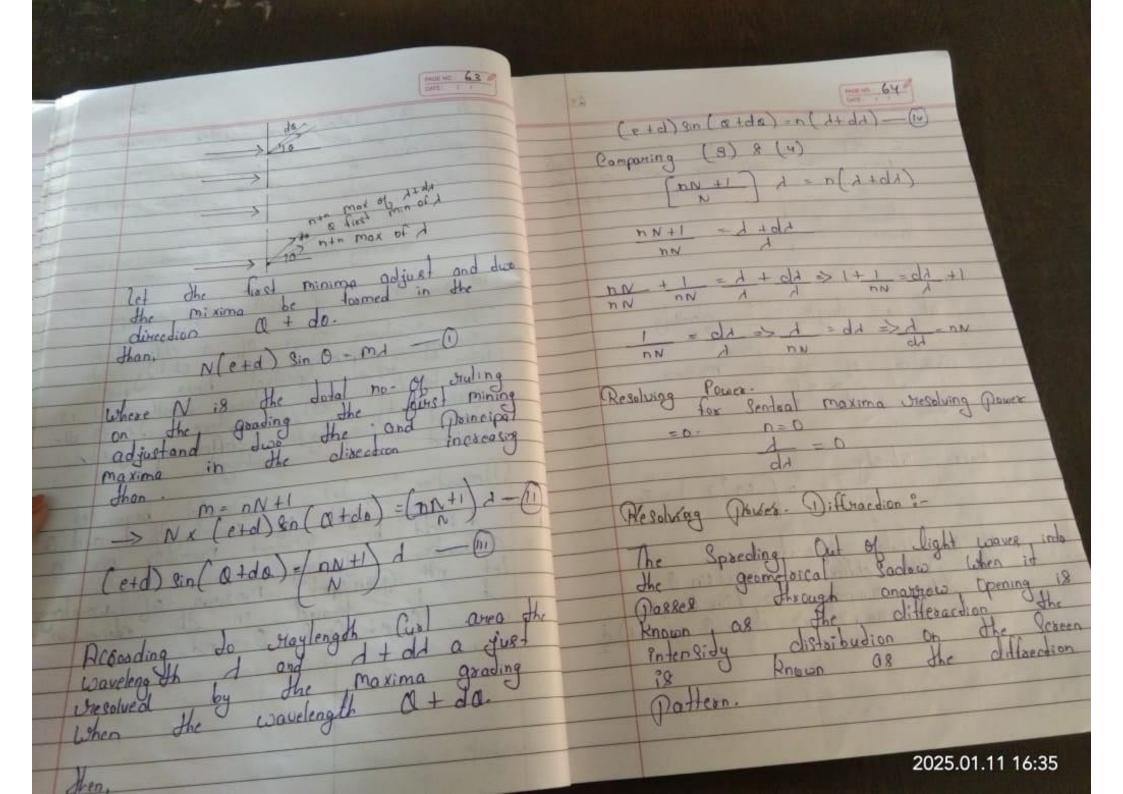


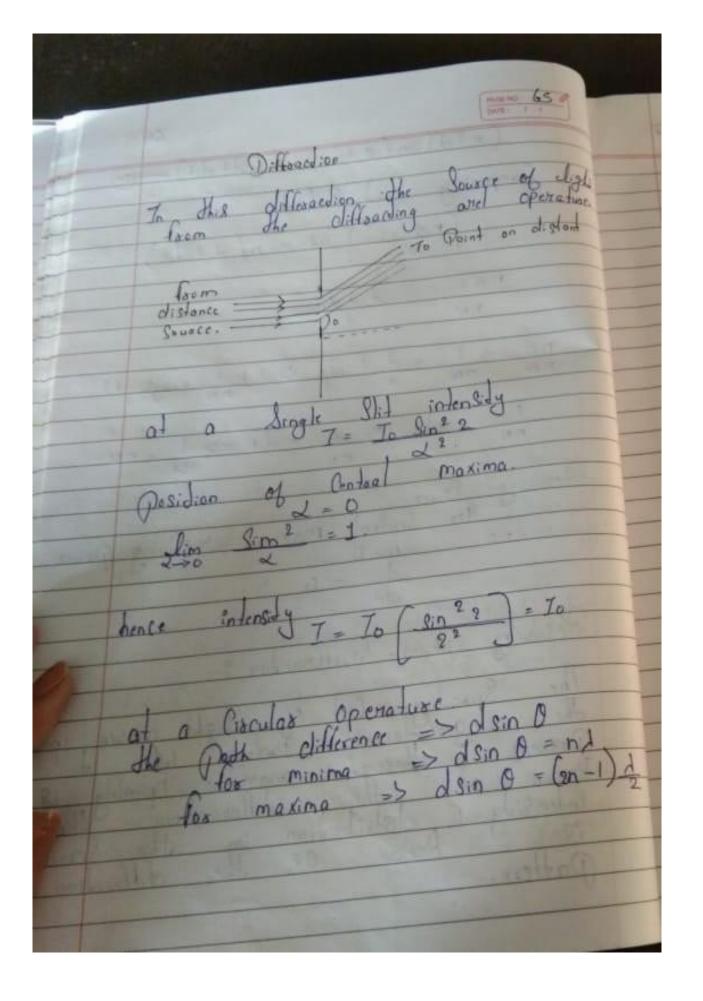












UNIT-3

Free Electron theory of metals

Classical free electron theory is based on the following postulates:

- 1. A solid metal is composed of atoms and the atoms have nucleus, around which there are revolving electrons.
- 2. In a metal the valance electrons of atoms are free to move throughout the volume of the metal like gas molecules of a perfect gas in a container
- 3. The free electrons move in a random directions and collide with either positive ions fixed to the lattice or other free electrons and collisions are elastic in nature i.e. there is no loss of energy.
- 4. The movement of free electrons obeys the classical kinetic theory of gasses. The mean K.E. of a free electron is equal to that of gas molecule $\begin{bmatrix} 3 & KT \end{bmatrix}$ $\begin{bmatrix} 1 & 1 & 1 \\ 1 & 1 & 1 \end{bmatrix}$.

- 5. The electron velocities in a metal obey Maxwe2ll-Boltzman distribution of velocities.
- 6. The free electrons move in a uniform potential field due to ions fixed in the lattice
- 7. When an electric field is applied to the metal the free electrons are accelerated. The accelerated electrons move in opposite direction of the applied.
- 8. The electric conduction is due to the free electrons only.

ROOT MEAN SOUARE (R.M.S.) VELOCITY:

Let \overline{C} be the r.m.s velocity of the free electron. then the $Kinetic\ energy = \frac{1}{2}mC^{\frac{2}{3}}$

Kinetic energy =
$$\frac{1}{2}mC^{2}$$

But according to the classical free electron theory the mean

Kinetic Energy =
$$\begin{bmatrix} \frac{3}{2}KT \end{bmatrix}$$
.
 $m\frac{1}{2}me^2 = \frac{3}{2}KT$
 $\Rightarrow \boxed{\overline{c} = \sqrt{\frac{3KT}{m}}}$ where $\overline{c} = \text{root mean square velocity}$

MEAN FREE PATH (λ) AND MEAN COLLISION TIME (τ_c)

The average distance travelled by an electron between two successive collisions in the presence of applied filed is known as 'Mean free path (λ) '.

The time taken by an electron between two successive collisions is known as "Mean Collision Time (τ_C) " of the electron

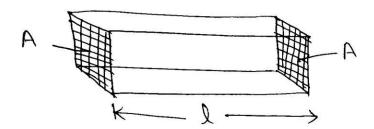
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$$\tau_{c} = \frac{\lambda}{\overline{c}} = \lambda \sqrt{\frac{m}{3KT}}$$

DRIFT VELOCITY (v_d) :

It is the average velocity acquired by the free electrons of a metal in a particular direction during the application of the electric field.

ELECTRICAL CONDUCTVITY IN METALS:



Let us consider a conductor of length l and area of cross section A

The volume of the conductor = Al

If there are n number of electrons per unit volume of the metal

then the total number of electrons in the metal = Aln

If e is the charge of the electron then the total charge q due to all electrons in the conductor is given by q = Aln.e

Let *t* be the time taken by the electron to move from one end to other end then

Current (I) =
$$\frac{ch \arg e}{time} = \frac{q}{t} = \frac{A \ln e}{t}$$

But $\frac{l}{t} = v$

$$mI = Anev_d$$

$$\Rightarrow v = \frac{I}{Ane} = \frac{J}{ne}$$

Where
$$J = \text{current density} = \frac{I}{A}$$

In a metal the current density J is given by the equation

$$J = nev_d$$
 (1)

Where n = number of electrons per Unit volume, e = electron charge and v_d = drift velocity

If E is the applied electric field then the electric force acting on a free electron is given by

$$F = eE \tag{2}$$

From Newton's IInd law F = ma ----- (3)

From (2) and (3) ma = eE

i.e.
$$a = \frac{eE}{m}$$

but $a = \text{drift velocity/collision time} = \frac{v_d}{\tau_c}$

$$v_d = a\tau_c = \frac{eE}{m}\tau_c$$

$$mJ = ne. \frac{eE}{m}\tau_c = \frac{ne^2E}{m}\tau_c \tag{4}$$

But from microscopic form of ohms law

$$J = \sigma E.....(5)$$

On comparing Eq(4)&(5)

m Conductivity
$$\sigma = \frac{ne^2}{m} \tau_c$$
 or Re sistivity.p = $\frac{m}{ne \tau_c}$

Conductivity may also be expressed in terms of mobility (μ) which is defined as drift velocity per unit electric field

$$\mu = \frac{v_d}{E} = \frac{e}{m} \tau$$

From (4)
$$\sigma = ne\mu$$

RELAXATION TIME(τ_r)

Under the influence of an external electric field free electrons attain a directional velocity of motion. If the field is switched off the velocity starts decreasing exponentially. Such a process that tends to restore equilibrium is called relaxation process.

If v_o is the velocity at t = 0 at which the field is switched off.

The velocity at any time is given by

$$v = v_o e^{\frac{-t}{\tau r}}$$

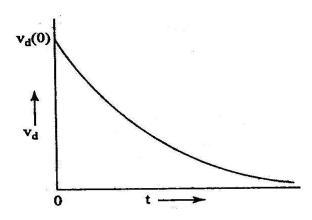
In the above expression τ_r = relaxation time

If
$$t = \tau_r$$

$$v = v e^{\tau_r} = v e^{-1} = \frac{v_o}{e}$$

mRelaxation time τ is defined as the time required for the electron to reduce its velocity to $\frac{1}{r}$ of

its initial value. (OR) time taken for the drift velocity to decay $\begin{pmatrix} 1 \\ - \end{pmatrix}$ of its initial value.



Failure of classical free electron theory:

- 1. The phenomena such as photo electric effect, Compton Effect and black body radiation could not be explained by classical free electron theory.
- 2. According to classical theory the value of specific heat of metals is given by 4.5R (R =Universal gas constant) where as the experimental value is nearly 3R(Dulong Petit law)
- 3. Electrical conductivity of semiconductor or insulator could not be explained by using this model.
- 4. According to classical free electron model $\frac{K}{\sigma T}$ is constant. (Widemann-franz law) as this not constant at low temperatures.
- 5. Ferromagnetism could not be explained by this theory
- 6. According to classical free electron theory,

Resistivity

$$p = \frac{m}{ne^2 \tau_c} = \frac{m}{ne^2} \sqrt{\frac{3KT}{m}} \frac{1}{\lambda} = \frac{\sqrt{3KTm}}{ne^2 \lambda}$$

$$p = \sqrt{T}$$

But according to experiments $p\alpha T$

OUANTUM FREE ELECTRON THEORY:

Sommerfield applied quantum mechanics to explain conductivity phenomenon in metals. He has improved the Drude- Lorentz theory by quantizing the free electron energy and retaining the classical concept of force motion of electrons at random.

ASSUMPTIONS

- 1. The electrons are free to move with in the metal like gaseous molecules. They are confined to the metal due to surface potential.
- 2. The velocities of electrons obey Fermi-Dirac distribution because electrons are spin half particles.
- 3. The electrons would go into different energy levels and obey Pauli's exclusion principle.

- 4. The motion of the electron is associated with a wave called matter wave, according to the deBroglie hypothesis.
- 5. The electrons can not have all energies but will have discrete energies according to the equation $E_{n=} \frac{n^2 h^2}{8ma^2}$ where a is the dimension of the metals.

Derive an expression for electrical conductivity by using quantum free electron theory

According to Quantum theory

$$p = mv = hK - - - (1) 2\pi$$
Where $h = \frac{1}{2\pi}$, $K = \frac{1}{\lambda}$

Differentiating equation (1) w.r.t to t

$$a = \frac{dv}{dt} = \frac{h}{m} \frac{dK}{dt}$$

At equilibrium the lorentz force F = -eE acting on the electron is equal and opposite to the product of mass and acceleration of the electron i.e.

$$eE = ma$$

$$h \ dK$$

$$\Rightarrow m \underline{\hspace{1cm}} = eE$$

$$m \ dt$$

$$\Rightarrow dK = \frac{eE}{h} dt ---(2)$$

Integrating (2) between the limits 0 and t

$$\int dK = \int \frac{eE}{h} dt$$

$$K(t) - K(0) = \frac{eE}{h} t$$

$$EK = \frac{eE}{h} t$$
where t_c = men collision time.

But $J = ne$ and
$$Ev = h$$

From microscopic form of Ohm's law

$$J = \sigma E$$

$$m\sigma = \frac{ne^2t}{m^*}$$
This is the expression for the electrical conductivity.

FERMI DIRAC DISTRIBUTION:

In quantum theory different electrons occupy different energy levels at O'K. Electrons obey Pauli's exclusion principle. As the electrons receive energy they are excited to higher levels which are unoccupied at O K. The occupation of electrons obeys Fermi-Dirac distribution law. The particles that obey Fermi-Dirac distribution law are called Fermions.

The Fermi-Dirac distribution function at a temperature T is given by

$$f(E) = \frac{1}{e^{(E-E_f)/KT} + 1}$$

Where E_f = Fermi energy, f(E) = the probability that a state of energy (E) is filled.

(I) At T=O K for
$$E > E_f$$
 $E = \frac{n^2h^2}{8ma^2}$
$$f(E) = \frac{1}{e^{\frac{1}{2}} + 1} = 1$$

This means that all the energy state below E_f are filled.

For $E > E_f$

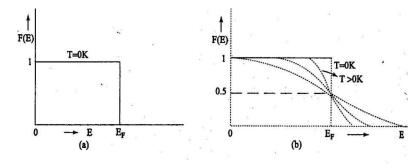
$$f(E) = \frac{1}{e^{1/2} + 1} = 0$$
 Means that all the energy levels above E_f are empty.

From this we define Fermi level as it is the level at 0K below which all the levels are filled and above which all the levels are empty or it is the highest occupied state at 0K

(2) At T>0 and
$$E = E_f$$

$$f(E) = \frac{1}{1+1} = \frac{1}{2}$$

Fermi level is the state at which the probability of electron occupation is ½ at any temperature.



FERMI ENERGY:

The Fermi energy is a concept in quantum mechanics referring to the energy of the highest occupied quantum state in a system of Fermions at absolute zero temperature.

For the one dimensional infinite square well the energy of the particle is given by

$$E = \frac{n^2 h^2}{8ma^2}$$

Suppose now instead of one particle in this box we haven particles in the box and that particles are fermions with spin ½ then only two particles can have the same energy.i.e. Two particles have the same energy of

$$E_1 = \frac{h^2}{8ma^2}$$

Two particles having energy

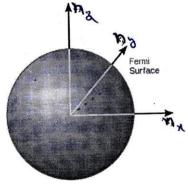
$$E_2 = \frac{4h^2}{8ma^2}$$

 \therefore All the energy levels up to n=N/2 are occupied and all the higher levels are empty.

$$E_f = E_{N/2} = \frac{(N/2)^2 h^2}{8ma^2} = \frac{N^2 h^2}{32ma^2}$$

$$E_f = \frac{N^2 h^2}{32ma^2}$$

DENSITY OF STATES



The number of states with energy less than E_f is equal to the number of states that lie within a sphere of radius $|n_f|$ in a region of K-space where n_x , n_y and n_z are positive.

$$mN = 2\mathbb{I} \quad \frac{1}{8} \quad \frac{4}{3} \quad m^{3}$$

$$mN = 2\mathbb{I} \quad \frac{1}{8} \quad \frac{4}{3} \quad f$$

$$mN = 2\mathbb{I} \quad \frac{1}{8} \quad \frac{4}{3} \quad f$$

$$m = 2\mathbb{I} \quad \frac{1}{8} \quad \frac{4}{3} \quad f$$

$$m = 2\mathbb{I} \quad \frac{1}{8} \quad \frac{4}{3} \quad f$$

$$m = \frac{3N}{1} \quad \frac{1}{1} \quad m^{3} = \frac{3N}{1} \quad m^{3} =$$

So the Fermi energy

$$E = \frac{h \pi n_f}{h \pi n_f} = \frac{h \pi}{m} (\underline{})^{3}$$

$$E = \frac{h \pi n_f}{m n_f} = \frac{h \pi}{m} (\underline{})^{3}$$

$$E_{f} = \frac{-h^{2} \pi}{2m \ a^{2}} (\frac{1}{\pi})^{3} = \frac{h^{2} \pi^{3} (3N)^{\frac{2}{3}}}{2m \ \frac{2}{(a^{3})^{3}}} = \frac{h^{2} \ 3N\pi^{\frac{2}{2}}}{2m \ a^{3}} = \frac{h^{2} \ 3N\pi^{\frac{2}{2}}}{2m \ a^{3}} = \frac{h^{2} \ 3N\pi^{\frac{2}{2}}}{2m \ v}^{\frac{2}{3}}$$

$$mN^{\frac{2}{3}} = \frac{2m}{(1 - 1)^{3}} \frac{V}{E_{f}}$$

$$\Rightarrow N = (\frac{2m}{h^{2}})^{\frac{3}{2}} \frac{V}{(1 - 1)^{2}} \frac{V}{E_{f}}$$

$$dN = 3 2m^{3} V$$

Therefore density of states: $D(E) = \frac{1}{dE} = \frac{1}{2} \left(\frac{1}{h^2}\right)^{\frac{7}{2}} \left(\frac{1}{3\pi^2}\right) E_f^{\frac{2}{2}}$ $D(E) = \frac{V}{2\pi^2} \left(\frac{2m^{\frac{3}{2}-1}}{h^2}\right)^{\frac{1}{2}} E_f^{\frac{2}{2}}$

Therefore the total number of energy states per unit volume per u₃nit energy range

$$Z(E) = \frac{D(E)}{V} = \frac{1}{2\pi^{2}} \frac{2m^{\frac{3}{2}}}{h^{2}} \frac{1}{E^{\frac{3}{2}}} \frac{(2m)^{\frac{3}{2}}}{2\pi^{2}} 8\pi^{3}E^{\frac{3}{2}}$$

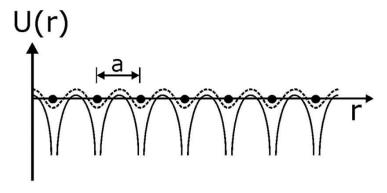
$$Z(E) = \frac{4\pi}{h^{3}} (2m)^{\frac{3}{2}} E^{\frac{1}{2}}$$

Therefore the number of energy states in the energy interval E and E + dE are

$$Z(E)dE = \frac{4\pi}{h^3} (2m)^{\frac{3}{2}} E_f^{\frac{1}{2}} dE$$

BAND THEORY OF SOLIDS

BLOCH THEORM:



Metals and alloys are crystalline in nature. When the electron move into the periodic ion core, it enters into the periodic potential i.e. potential is minimum at the positive ion sites and maximum between the two ions.

The one dimensional Schrödinger wave for this case is

$$\frac{6^2 \psi}{6x^2} + \frac{8\pi^2 m(E - V)}{h^2} \psi = 0$$

The periodic potential V(x) may be defined as

$$V(x) = V(x + a)$$

Bloch has shown that the one dimensional solution of the form

$$\psi(x) = e^{ikx}.u_k(x) = e^{ika}.u_k(a)$$

Where $u_k(x) = u_k(x + a)$

$$\psi\left(x+a\right)=e^{ik(x+a)}.u\left(x+a\right)$$

$$=e^{ikx}e^{ika}.u_k(x+a)$$

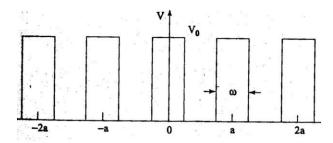
$$=e^{ika}e^{ikx}.u_{k}(x)$$

$$\psi(x+a) = e^{ika}\psi(x)$$

This is referred as Bloch condition.

KRONIG-PENNEY MODEL:

The free electrons in a metal move under a periodic potential due to regularly arranged positive ions. The nature of the energies of the electron is determined by solving Schrödinger wave equation. For simplicity, the periodic potential is taken in the form of regular o-ne dimensional array of square well potentials.



Within the wall the electron has potential energy

$$V = 0, 0 < x < a$$

Outside the wall the electron has the PE

$$V = V_0, -b < x < 0$$

m the Schrödinger wave equation for the two regions are

$$\frac{6^2 \Psi}{6x^2} + \frac{8\pi^2 mE}{h^2} = 0, 0 < x < a -----(1)$$

$$\frac{6^2 \psi}{6x^2} + \frac{8\pi^2 m(E - V)\psi}{h^2} = 0, -b < x < 0 - - - - - (2)$$

Let
$$\alpha^2 = \frac{8\pi^2 mE}{h^2}$$

And $\beta^2 = \frac{8\pi^2 m(V - E)}{h^2}$

Then (1) and (2) becomes

$$\frac{6^2 \Psi}{6x^2} + \alpha^2 \Psi = 0,$$
 (3)

$$\frac{6^2 \Psi}{6x^2} - \beta^2 \Psi = 0, \tag{4}$$

On solving equations (3) and (4) and by applying Bloch Theorem we get

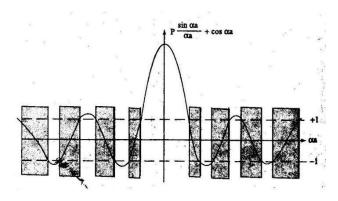
$$P \frac{\sin \alpha a}{\alpha a} + \cos \alpha a = \cos ka$$
 ----(5)

Where
$$P = \frac{mabV_0}{h^2}$$

and
$$\alpha^2 = \frac{8\pi^2 mE}{h^2} \Rightarrow E = \frac{h^2 \alpha^2}{8\pi^2 m}$$

The nature of the equation is illustrated by the plot i.e. drawn between $P = \frac{\sin \alpha a}{\alpha a} + \cos \alpha a$ and

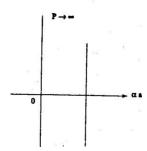
 αa and at the same time the RHS having the value between +1 and -1



In the above graph only some of the range of αa values are allowed indicating the a limiting range of energies are allowed. Allowed energy region is indicated by dark region and the forbidden region is indicated by dotted lines.

Special cases:

(i) If $P \to \mathbb{Z}$ the allowed band reduces to single energy level. This is the special case of electron trapped.



(ii) If
$$P \rightarrow 0$$

 $\cos \alpha a = \cos ka$
 $k = \alpha$

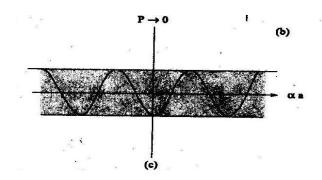
$$k^2 = \alpha^2 = 8\pi^2 mE \implies E = \frac{h^2 k^2}{2} = \frac{h_2^2}{4\pi^2}$$

$$\Rightarrow E = \frac{h^2}{2m h^2} = \frac{1}{2m v^2} 8\pi m \quad 8\pi m \lambda^2$$

Therefore Total energy =KE+PE

 \Rightarrow Potential Energy V = 0

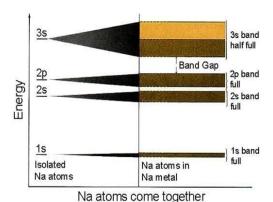
And this is the case of free electron.



Finally we conclude that

- (i) Electrons in solids are permitted to be in allowed energy bands separated by forbidden energy gaps.
- (ii) Allowed energy band width increases with αa
- (iii) $P \rightarrow \boxed{2}$ is the case of electron trapped and
- $P \rightarrow 0$ is the case of classical free particle

ORIGIN OF ENERGY BANDS:



In an isolated atom the electrons are tightly bound and have discrete sharp energy levels. When two identical atoms are brought closure the outermost orbit of these atoms overlaps and interacts. Then the energy levels corresponding to those atoms are split into two. If more atoms are brought together more levels are formed and for a solid of N atoms each of energy levels of an atom split into N levels of

Depends on the degree of overlap of electrons of adjacent atoms and is largest for outermost atomic electrons.

The electrons in the inner shells are strongly bound to their nucleus while the electrons in the outer most shells are not strongly bound to the nucleus. The electrons in the outermost shell are called valance electrons. The band formed by the energy levels containing the valance electrons is known as valence band.

Valence Band:

The band formed by the energy levels of valence electrons is called valence band. Or the band having highest occupied band energy. It may be partial or completely filled.

Conduction band:

This is the lowest unfilled energy band. This is empty or partially filled.

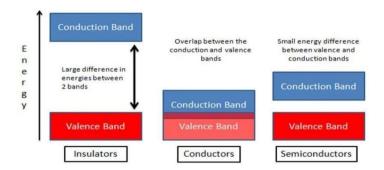
Forbidden Energy gap:

The conduction band and valence band are separated by a region or gap known as forbidden band. In this there is no electron exist.

CLASSIFICATION OF MATERIALS INTO CONDUCTORS, SEMICONDUCTORS AND INSULATORS:

INSULATOR:

In case of insulators the forbidden band is wide. Due to this free electrons cannot jump from valence band to conduction band. In insulators the energy gap between Valence and conduction band is of the order of 10eV.

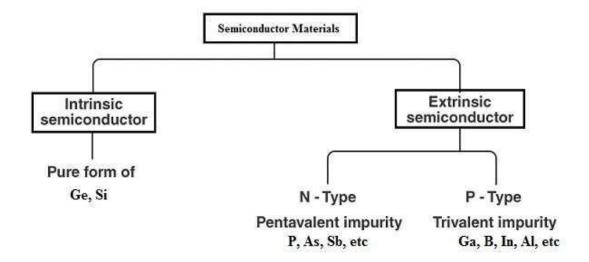


CONDUCTORS:

In case of conductors there is no forbidden band the valence band and conduction band overlap each other. Here plenty of electrons are available for electronic conduction.

SEMICONDUCTORS:

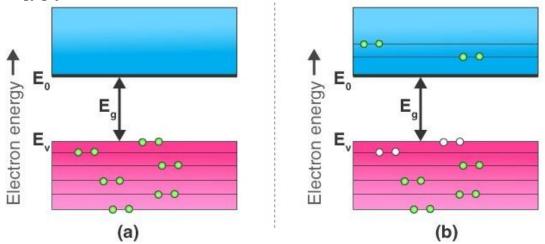
In semiconductors there is small forbidden band exist between valence band and conduction band. In semiconductors forbidden band gap is between 0.7 to 1.1 eV. For semiconductors the electrical properties lie between insulators and good conductors.



Intrinsic Semiconductors

The intrinsic semiconductors are the semiconductors are elemental semiconductors or also called as pure semiconductors. These semiconductors are made up of one kind of atoms only. The examples of intrinsic semiconductors are Silicon (Si) and Germanium (Ge).

At T=0 K the intrinsic semiconductor behaves as insulators. Because no electron exists in the conduction band. But at ordinary temperatures due to thermal agitations the covalent bonds are broken and some electrons move to conduction band. The Fermi energy level inside an intrinsic semiconductor lies in the middle of energy gap.



(a) Intrinsic Semiconductor at T = 0 Kelvin, behaves like an insulator (b) At t>0, four thermally generated electron pairs

Extrinsic Semiconductors

By doping suitable impurity in the intrinsic semiconductors. Thus obtained semiconductors are called as extrinsic semiconductors. Depending upon the type of impurity added the extrinsic semiconductors can be classified as N-type and P-type semiconductors.

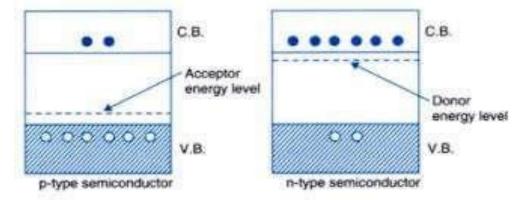
N-type Semiconductors

When intrinsic semiconductors either Si or Ge are doped with pentavalent material, then the obtained semiconductor material is called N-type semiconductor. The Si or Ge are tetravalent materials hence the four electrons in the outer shell of these materials forms the covalent bond with another Si or Ge atoms to complete their octet. When a pentavalent impurity Like Arsenic (As) is added to the Si or Ge then the four out of five valance electrons are shared by the host atoms(Si or Ge) while the fifth electrons of the impurity is loosely bound to its parent atom. These loosely bound electrons give rise to donor levels. At ordinary temperature all the electrons of the donor level move to the conduction band.

P-type Semiconductors

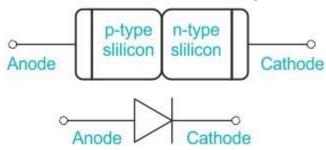
When intrinsic semiconductors either Si or Ge are doped with trivalent material, then the obtained semiconductor material is called P-type semiconductor. When a trivalent impurity Like Arsenic (Al) is added to the Si or Ge then the three valance electrons of impurity atom is shared by the host atoms (Si or Ge) and one of the electrons of host atom remain unshared. This result in the deficiency of an electron .Thus electron

deficiency exists in valance band just above the conduction band and are called as acceptor levels.



PN Junction Diode

An interface or a boundary within a semiconductor device, between the P-type and the N-type semiconductor material, is called the PN junction.



Formation of PN Junction Diode

In a PN junction diode, an ionized donor is left behind on the N-side when an electron diffuses from the N-side to the P-side and a layer of positive charge develops on the N-side of the junction. When a hole moves from the P-side to the N-side, an ionized acceptor is left behind on the P-side, causing a layer of negative charges to accumulate on the P-side of the junction. The depletion area is defined as a region of positive and negative charge on each side of the junction. An electric field with a direction from a positive charge to a negative charge develops on either side of the junction.

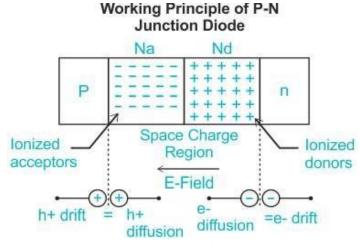


Fig- Construction Diagram of PN Junction Diode

The electric potential between P and N-regions changes when an external potential is supplied to the PN junction terminals. As a result, the flow of the majority of carriers is altered, allowing electrons and holes to diffuse through the PN junction.

The diode is thought to be in the forward bias state if the applied voltage reduces the width of the depletion layer, and reverse bias if the applied voltage increases the width of the depletion layer. The diode is said to be in the zero bias or unbias state if the breadth of the depletion layer remains unchanged.

VI Characteristics of PN Junction Diode

The relationship between the voltage across the junction and current through the circuit is known as the volt-ampere (VI) characteristics of a PN junction diode or semiconductor diode. Normally, voltage is measured along the x-axis, whereas the current is measured along the y-axis.

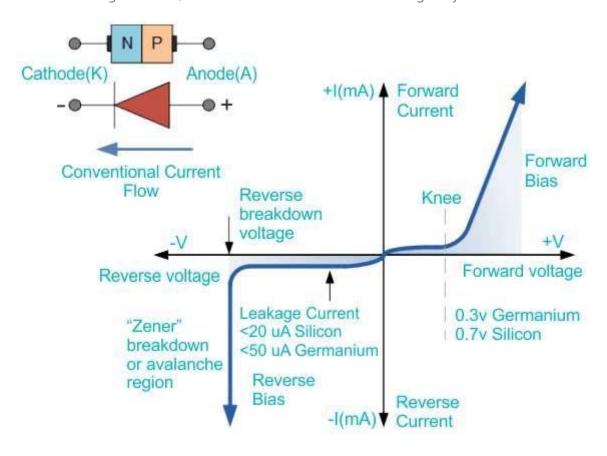


Fig- VI Characteristics of PN Junction Diode

The VI characteristics of PN junction diode can be explained in three cases:

- Zero bias or unbias
- Forward bias
- o Reverse bias

Zero bias or unbias

No movement of holes or electrons occurs at zero bias state as no potential is applied externally which prevents the passage of electric current to flow in the diode.

Forward Bias

When the p-type is connected to the battery's positive terminal and the n-type to the negative terminal, then the P-N junction is said to be forward-biased.

Reverse Bias

When the p-type is connected to the battery's negative terminal and the n-type is connected to the positive side, the P-N junction is reverse biased.

Breakdown

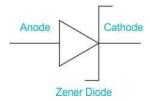
In reverse biasing, when the applied potential is increased it leads to abrupt increase of reverse current this is called as breakdown. Two kind of mechanism are responsible for the abrupt current change

- 1. Avalanche breakdown This kind of break down occurs when the impurity concentration is lower. The increase in the reverse applied potential does not leads to increase in the current but increase in the potential results in the increase in the kinetic energy of electron, when electron acquires the kinetic energy of the order of the strength of covalent bond then this electron breaks the covalent bond of the atom resulting in the electron hole pair. Thus produced electrons get accelerated and break another covalent bond and the process continues in the generation of large number of current carriers and large current starts to flow across the junction. The avalanche breakdown results in the damage of diode.
- **2. Zener breakdown** This kind of break down occurs when the impurity concentration is higher. The increase in the reverse applied potential does not leads to increase in the current but increase in the potential results in the widening of depletion layer. Thus a large electric field is set across junction, when the strength of internal field is of the order of the strength of covalent bond then this field breaks the covalent bond of the atoms resulting in the generation of large number of electron hole pairs and large current starts to flow across the junction. The zener breakdown does not damage the diode. When reverse potential is removed then the diode acquires its original state. The breakdown curve in this case is sharp near breakdown voltage.

S. No.	Zener Breakdown	Avalanche Breakdown
1.	This takes place in a very thin junction	This takes place in a thicker junction (the
	(the depletion layer is narrow).	depletion layer is wide).
2.	This is observed in zener diodes at	This is observed in zener diodes at V _z
	$V_z \sim 6 \text{ V (or less)}.$	greater than 6 V.
3.	In this, the carrier increase is the result	In this, the carrier increase is the result
	of electric field strength (about 2×10^7 V/m).	of collisions.
4.	V-I characteristics with the zener breakdown	V-I characteristics with the avalanche
	is very sharp at V_{\cdot} .	breakdown is gradual near V_z .
5.	The breakdown voltage decreases with	The breakdown voltage increases with
	increase in temperature.	increase in temperature.
6.	Zener breakdown does not result in the	Avalanche breakdown destroys the diode.
	destruction of the diode.	

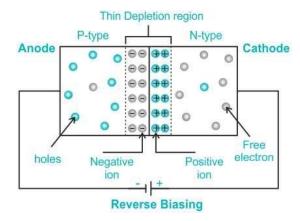
What is a Zener Diode?

A Zener diode can be defined as a heavily doped semiconductor device that is designed to operate the electric circuit in the reverse direction. It is also called a breakdown diode. It is a heavily doped semiconductor diode that is designed to operate the electric circuit in the reverse direction.



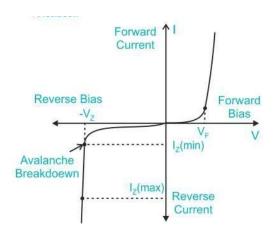
Working Principle of Zener Diode

The working principle is such that if the reverse bias voltage is less than the breakdown voltage, or if it is forward biased then it acts as an ordinary diode. This means that forward bias allows current to flow and reverse bias blocks the current from flowing. After this, the voltage surpasses the breakdown point in reverse bias, and the diode falls in the Zener region, where it gets conducted without getting damaged. Current in this region is known as avalanche current but for a Zener diode, it is also known as a Zener current.



Further, by controlling the amount of doping of the semiconductor material and by doing this the thickness of the depletion region in the PN junction and the breakdown voltage can be set to any value according to the need of the appliance.

V-I Characteristics of Zener Diode



The V-I characteristics of a Zener diode are divided into two parts which are mentioned as follows:

Forward Characteristics of Zener Diode

The first quadrant of the graph depicts the forward characteristics of a Zener diode, and from which we can understand that it is almost similar to the forward characteristics of any other normal PN junction diode.

Reverse Characteristics of Zener Diode

When a reverse voltage is applied to a Zener voltage, a small reverse saturation current which is lo lo flows across the whole diode. This current is present due to thermally generated minority carriers present in the diode. As the reverse voltage starts to increase, at a certain value of reverse voltage the reverse current also starts to increase drastically and sharply. The breakdown in the diode has occurred. This voltage is known as breakdown voltage in zener diode or Zener voltage and is denoted by V_zV_z .

Applications of Zener Diode

The uses of a Zener diode are mentioned as follows:

- Zener Diode as Voltage Regulator
- Zener Diode in Over-Voltage Protection
- Zener Diode in Clipping Circuits

3.13 HALL EFFECT

Definition. When a metal or a semiconductor carrying a current I is placed in a transverse magnetic field B, a potential difference is produced in the direction normal to both the current and magnetic field directions. This phenomenon is called **Hall effect**.

Hall effect measurements showed that it is the negative charge carriers namely electrons that are responsible for electrical conduction in metals. It also showed that there exists two types of charge carriers in semiconductors.

Importance. The importance of Hall effect is that it helps to determine the:

- (i) sign of charge carriers,
- (ii) charge carriers concentration and
- (iii) mobility of charge carriers if conductivity of the material is known.

Experimental Determination of Carrier Concentration and Mobility

Let us consider an n-type semiconductor in which the conduction is predominated by electrons. Suppose an electric current j flows in the positive x-direction and a magnetic field B is applied normal to this electric field in z-direction (Fig. 3.29). A force, called the Lorentz force is exerted on each electron which causes the electron paths to bend. As a result of this, the electrons accumulate on one side of the slab and are deficient on the other side.

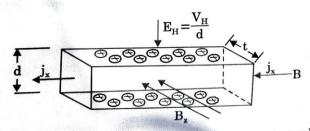


Fig. 3.29. Schematic view of an n-type semiconductor bar.

Thus, an electric field is created in the y-direction which is called the Hall field. In equilibrium condition Hall Force = Lorentz force

$$F_H = F_L$$

 $-qE_H = v_x B_z q$
with of the electrons, and q the electronic charge ...(75)

where $\boldsymbol{v}_{\boldsymbol{x}}$ is the velocity of the electrons, and \boldsymbol{q} the electronic charge

$$E_H = v_x B_z \qquad ...(76)$$

As current density $j_x = -Nv_x q$

$$\left(\text{Putting } v_x = \frac{E_H}{B_s}\right)$$

$$j_x = -\frac{NE_H q}{B_z}$$

$$N = -\frac{j_x B_z}{q E_H} = -\frac{j_x B_z}{q (V_H / d)}$$
 ...(77)

$$V_H = -\frac{j_x B_z d}{Nq} = -\frac{I B_z d}{NqA} \qquad ...(78)$$

[A = Area of cross-section of end face]

If t is the thickness of the semiconductor specimen, A = dt and the above equation reduces to

$$V_H = -\frac{B_z I}{Nqt} \qquad ...(79)$$

Hall field per unit current density per unit magnetic induction is called Hall coefficient R_H. Thus,

$$R_H = \frac{E_H}{J_x B_z} = + \frac{V_H / d}{j_x B_z} = - \frac{B_z I}{j_x B_z d \cdot Nqt}$$

$$R_H = - \frac{1}{Nq} \qquad ...(80)$$

In terms of Hall coefficient, Hall voltage is given by

$$V_H = R_H \frac{BI}{t} \tag{81}$$

The sign of the Hall coefficient R_H indicates whether electrons or holes predominate in the uction process conduction process.

If R_H = negative, then electrons are the predominant charge carriers.

If R_H = positive, then holes are the predominant charge carriers.

The electron mobility is given as

$$\mu_n = \frac{\sigma}{N|q|}$$

Hence

$$N|q|$$

$$\mu_n = |R_H| \sigma$$
...(82)

Thus, the magnitude of μ_n may also be determined if the conductivity σ has also been sured. measured.

INTKU-

The net electric field E is the semiconductor is a vector sum of E_x (electric field component The new Flow of E_x (electric field component in x-direction) and E_H (Hall field). It acts at an angle θ_H to the x-axis. θ_H is called the Hall angle.

From Fig. 3.30.

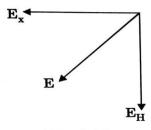


Fig. 3.30.

$$\tan \theta_H = \frac{E_H}{E_x} \qquad \dots (83)$$

 $E_H = \frac{V_H}{d} = \frac{B_z / j_x}{N|q|}$ As

...(85)

...(84)

Also

:.

$$\tan \theta_H = \frac{B_z}{N|q|\rho}$$

 $E_x = \rho j_x$

 $\left[\because \sigma = \frac{1}{\sigma} \right]$

 $\tan \theta_H = \sigma R_H \, B_z$ The product σR_H is designated as μ_n the mobility of electrons.

 $\tan \theta_H = \mu_n B_z$

...(86) $\theta_H = \tan^{-1} \left(\mu_n \, B_z \right)$

In the above discussions it is assumed that all carriers travel with a mean speed $\boldsymbol{v}_{\boldsymbol{x}}$. However this does not happen. As a result, the value of R_H gets modified. The appropriate value is

$$R_H = \frac{3\pi}{8} \left(-\frac{1}{Nq} \right) \tag{87}$$

Accordingly,

$$\mu_n = \left(\frac{8}{3\pi}\right) \sigma R_H \qquad \dots (88)$$

Applications:

- 1. Hall effect can be used for the measurement of the strength of magnetic field
- 2. It is used for the determination of carrier concentration of semiconductors
- 3. The sign of Hall coefficient tells about the predominant charge carriers in a semiconductor
- 4. Hall effect can be used for the amplification of weak signals

3.12 SOLAR CELL

The solar cell (or photovoltaic cell), is a device which converts light energy into electrical energy. This is an important photovoltaic device and is basically a p-n junction with a large surface area.

The high-efficiency solar cell was first developed by Chapin, Fuller and Pearson in 1954 using a diffused silicon p-n junction. Since then, solar cells have been developed and produced with polysilicon, CdTe and GaAs. In past four decades, a remarkable progress has been made.

Megawatt solar power generating plants have been built, solar cells are being combined with building materials, and are now the most important long-duration power supply for satellites and space vehicles. Over 95% of solar cells in production are silicon based.

A solar cell can deliver powers of the order of 1 kW/m². The schematic of the typical junction solar cell, with its top finger contacts, is shown in Fig. 3.27(a). The photovoltaic energy conversion process may best be expressed by the equivalent circuit shown in Fig. 3.37(b). An ideal diode is connected in parallel with a constant current (or voltage) source, which represents the photovoltaic energy generated, and with a load resistor.

(A) Basic Characteristics

The solar cell as shown in Fig. 3.27(a) consists of a shallow p-n junction formed by diffusion or epitaxy, on the surface a front ohmic contact stripe and fingers, and a back ohmic contact which covers the entire back surface. Fig. 3.27(b) represents the simplest equivalent circuit of the cell and contains the constant current source I_{ph} , the load current I, and the reverse saturation current of the diode I_s .

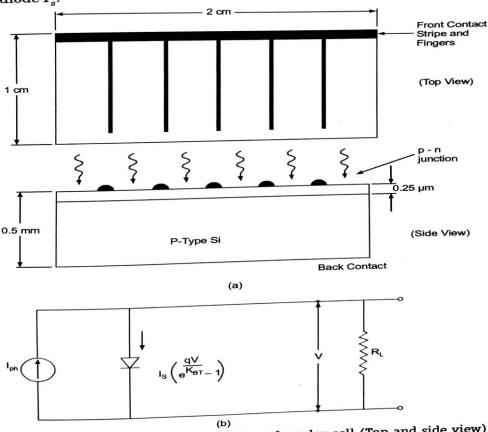


Fig. 3.27. (a) Schematic representation of a solar cell (Top and side view).

(b) The idealized equivalent circuit of a solar cell.

$$I = I_s \left[e^{\frac{qV}{kT}} - 1 \right] - I_{ph} \tag{68}$$

A plot of Eqn. (68) is shown in Fig. 3.28(a). For $I_{ph}=0.1$ amp, $I_s=10^{-9}$ amp, and $T=300^{\circ}$ K. As shown in the plot, the curve passes through the fourth quadrant and therefore that K. As shown in the plot, the curve passes and the properly choosing a load, it is possible to extract power can be extracted from the device. By properly choosing a load, it is possible to extract power can be extracted from the device. By properly choosing a load, it is possible to extract power can be extracted from the device. By properly choosing a load, it is possible to extract power can be extracted from the device. By properly choosing a load, it is possible to extract power can be extracted from the device. By properly choosing a load, it is possible to extract power can be extracted from the device. By properly choosing a load, it is possible to extract power can be extracted from the device. By properly choosing a load, it is possible to extract power can be extracted from the device. power can be extracted from the device. E_{sc} is the short-circuit current and V_{oc} is the open close to 80% of the product $I_{sc} \times V_{oc}$ where I_{sc} is the short-circuit current and V_{oc} is the open. close to 80% of the product $I_{sc} \times V_{oc}$ where $I_{sc} \times V_{oc}$ where circuit voltage of the cell, as shown by the financial voltage for the maximum power output quantities I_{mp} and V_{mp} which defines to the current and voltage for the maximum power output $(P_m = I_{mp} \times V_{mp})$ respectively.

Using Eqn. (68), we obtain for the open-circuit voltage

$$V_{oc} \equiv V_{\text{max}} = \frac{kT}{q} \ln \left(\frac{I_{ph}}{I_s} + 1 \right) \cong \frac{kT}{q} \ln \left(\frac{I_{ph}}{I_s} \right) \qquad ...(69)$$

The output power is given by

$$P = IV = I_s V \left(e^{\frac{qV}{kT}} - 1 \right) - I_{ph} V \qquad ...(70)$$

For maximum output power; $\frac{\partial P}{\partial V} = 0$

$$0 = I_s \left\{ V e^{\frac{qV}{kT}} \cdot \frac{q}{kT} + e^{\frac{qV}{kT}} \right\} - I_s - I_{ph}$$

$$\frac{I_{ph}}{I_s} = \frac{qV}{kT} e^{\frac{qV}{kT}} + e^{\frac{qV}{kT}} - 1$$

For maximum power $V = V_{m_n}$

$$\left(1 + \frac{I_{ph}}{I_s}\right) = \exp\left(\frac{qV_{mp}}{kT}\right) \left[1 + \frac{qV_{mp}}{kT}\right]$$

$$V_{mp} = \frac{kT}{q} \ln\left[\frac{(1 + I_{ph} / I_s)}{1 + (qV_{mp} / kT)}\right]$$
...(71)

and

$$\begin{split} I_{mp} &= \left[I_s \left(e^{\frac{qV_{mp}}{kT}} - 1 \right) - I_{ph} \right] \\ &= I_s \frac{qV_{mp}}{kT} e^{\left(\frac{qV_{mp}}{kT} \right)} \end{aligned} \dots (72)$$

Maximum Power Output, $P_{mp} = I_{mp} \times V_{mp}$ The **efficiency** of solar energy conversion is given then by

$$\eta = \frac{\text{maximum power output}}{\text{power input}} = \frac{I_{mp}V_{mp} / \text{cm}^2}{P_{\text{in}} / \text{cm}^2}$$

INTRODUCTION

$$\eta = \frac{I_{ph} \ qV_{mp}^2}{kT \left(1 + \frac{qV_{mp}}{kT}\right) A} \left(1 + \frac{I_s}{I_{ph}}\right) \frac{1}{P_{\text{in}} / \text{cm}^2} \qquad ...(73)$$

where A is the exposed front area of the solar cell and P_{in}/cm^2 is the solar power density outside the atmosphere.

The I-V curve is more generally represented by Fig. 3.28(a) which is simply an inversion of Fig. 3.28(b) about the voltage-axis.

Fill factor of a solar cell is defined as

$$FF = \frac{I_{mp}V_{mp}}{I_{ph}V_{oc}} \qquad ... (74)$$

The fill factor is the ratio of the maximum power rectangle [Fig. 3.28(b)] to the rectangle of $I_{ph} \times V_{oc}$. In most solar cells the fill factor is ~ 0.7.

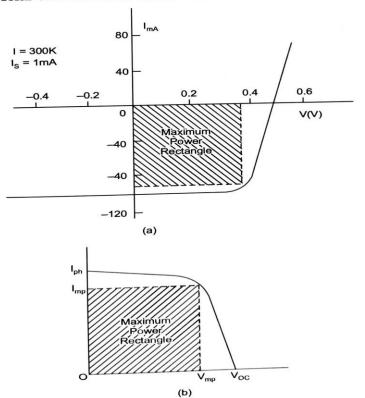
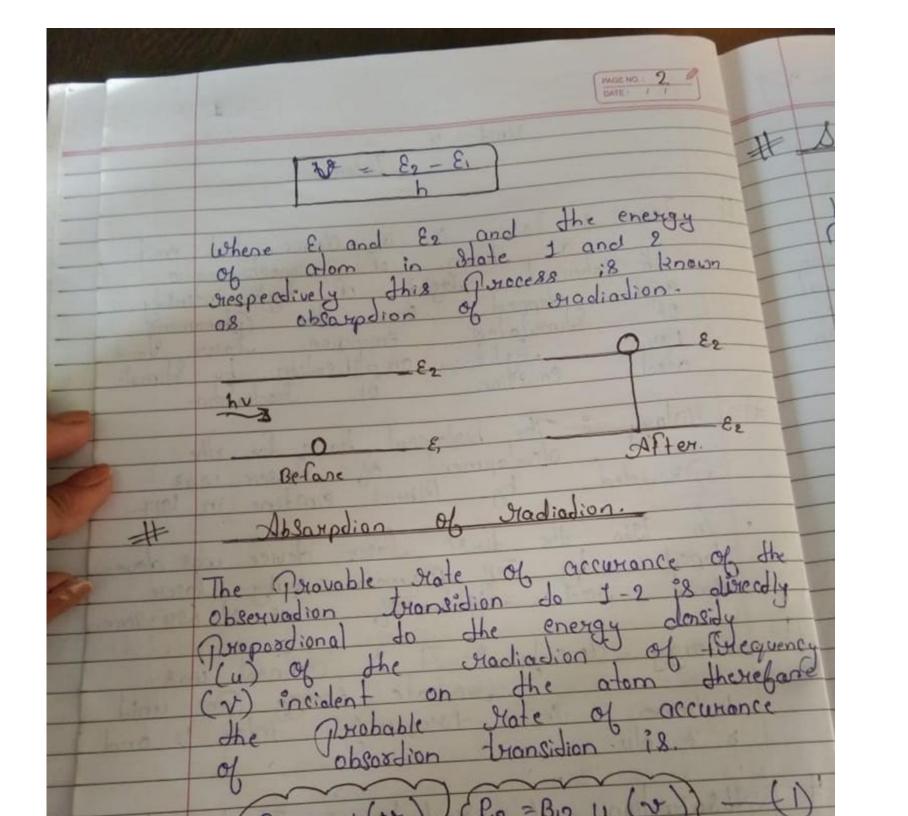


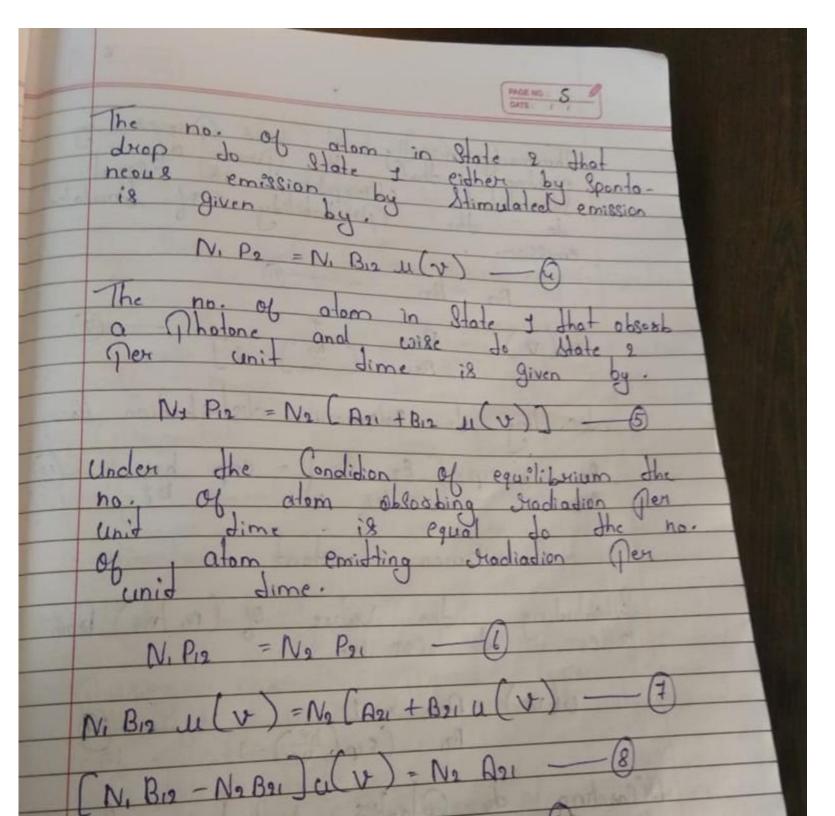
Fig. 3.28. (a) Current-voltage characteristics of a solar cell under illumination (b) Inversion of (a) about the voltage axis.

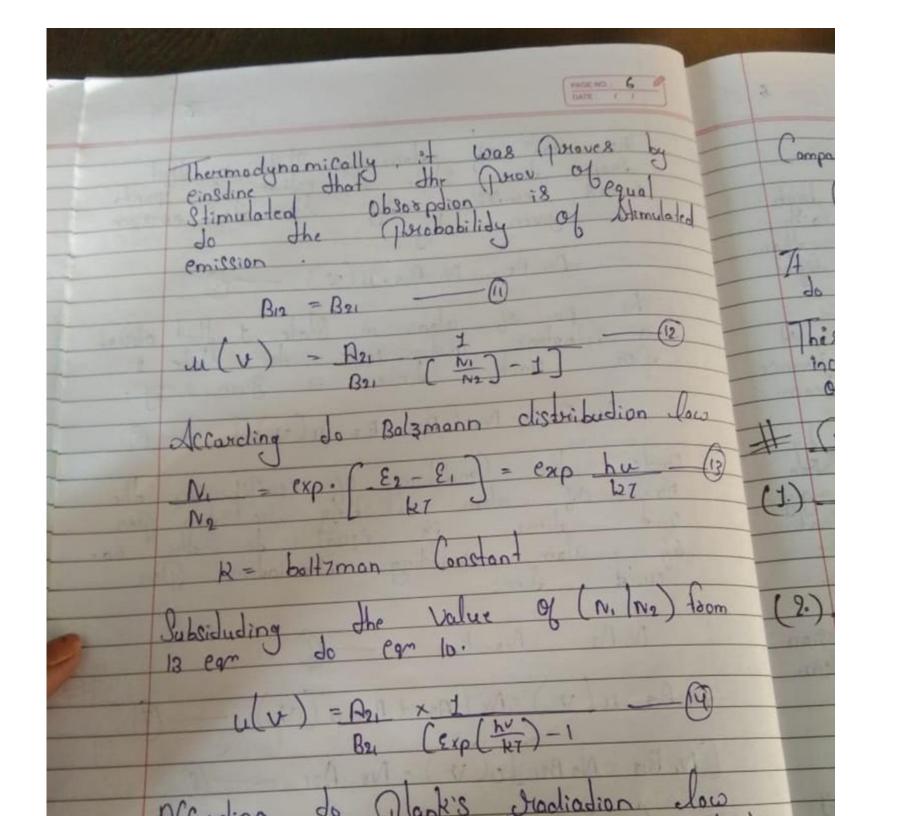
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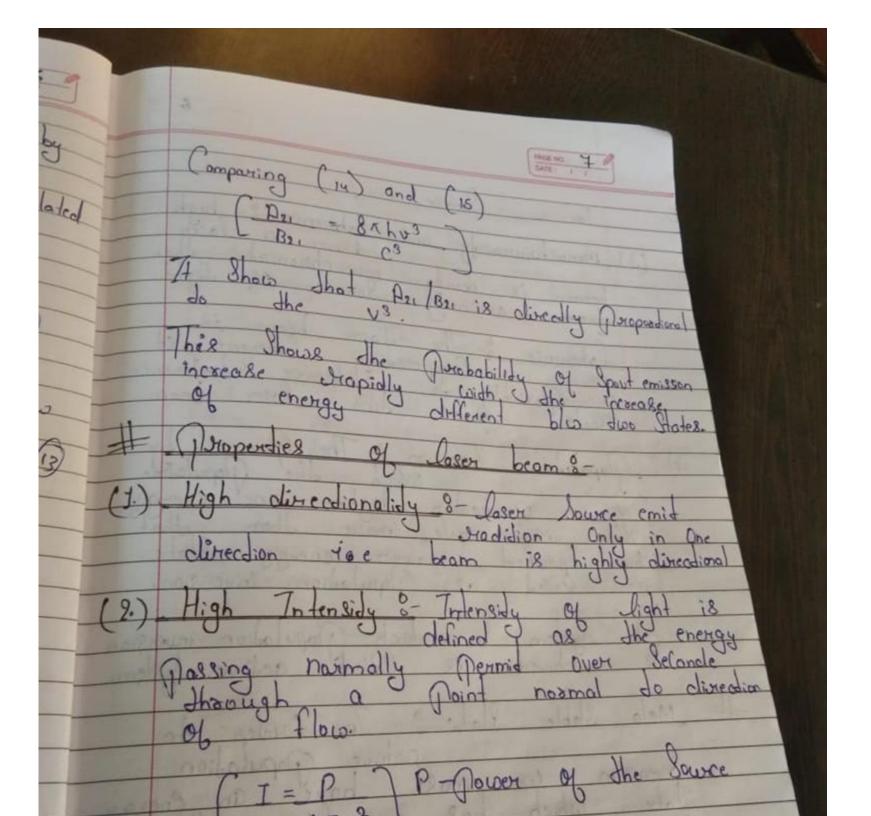


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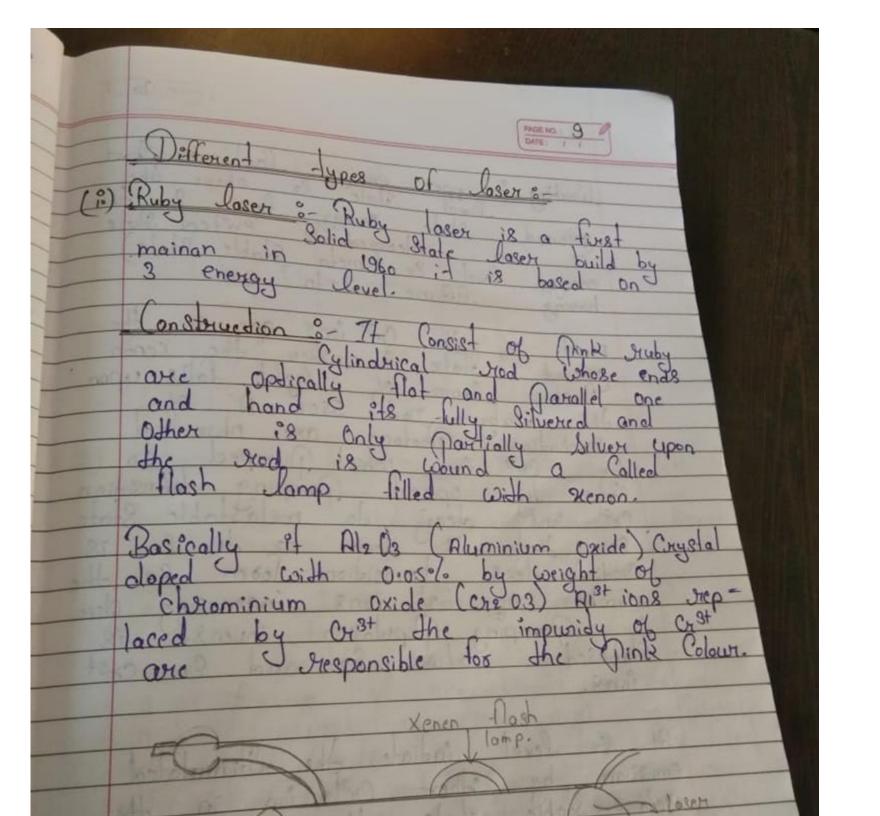
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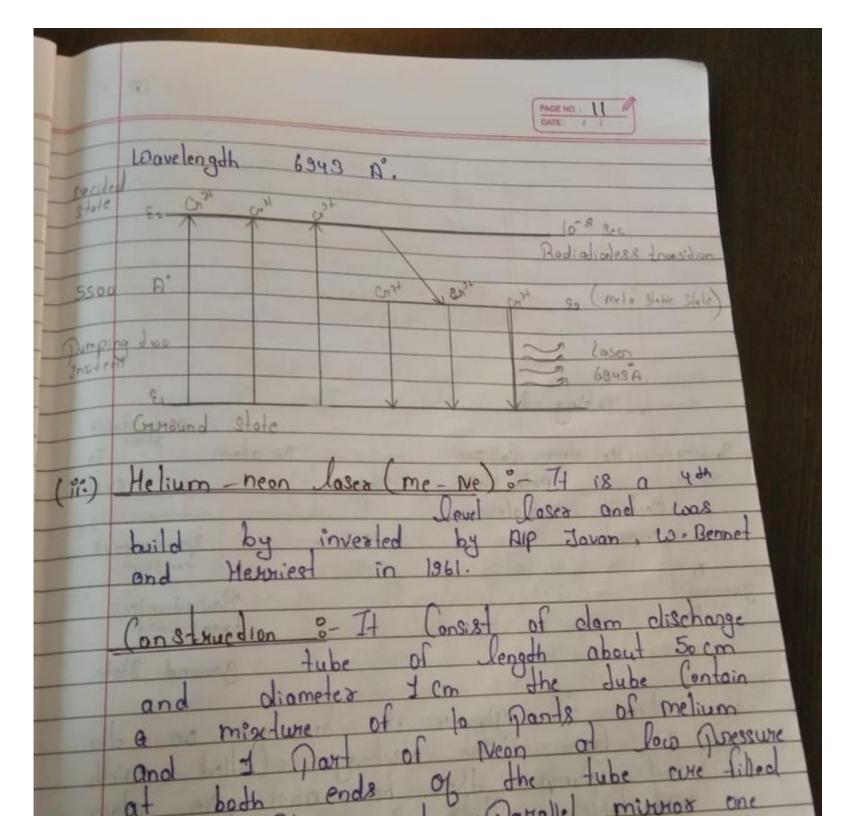
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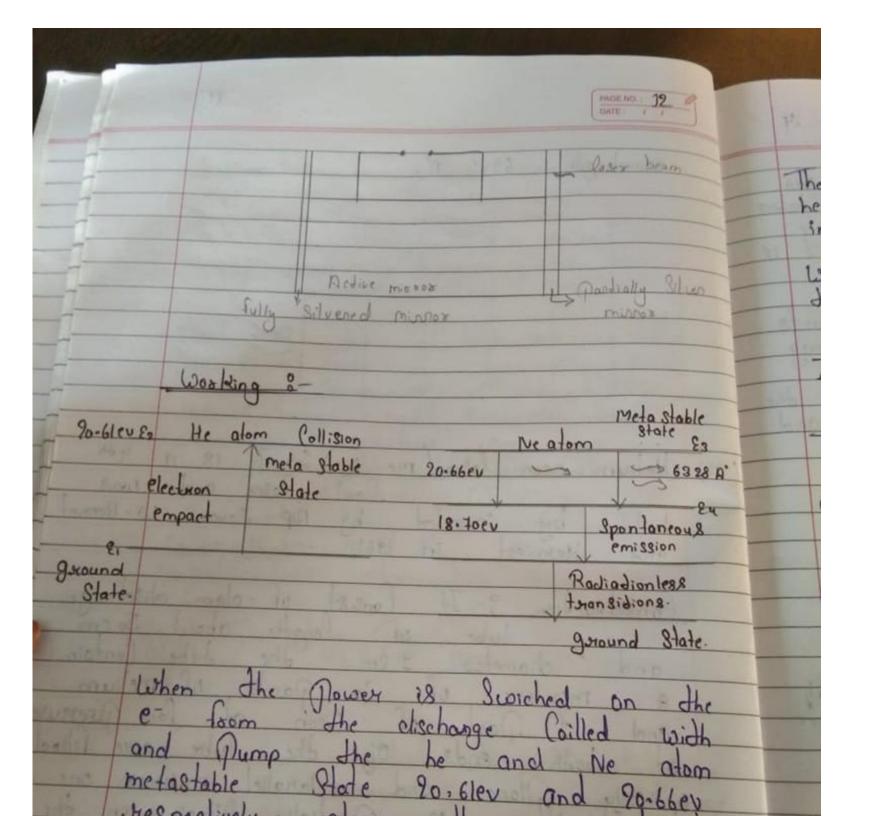
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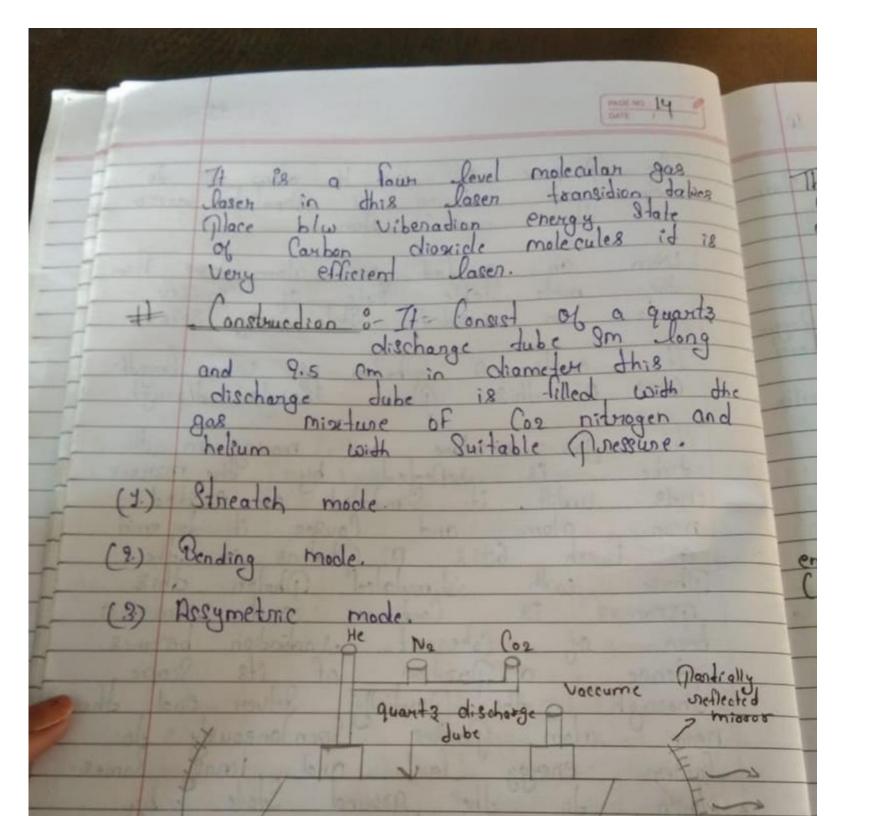
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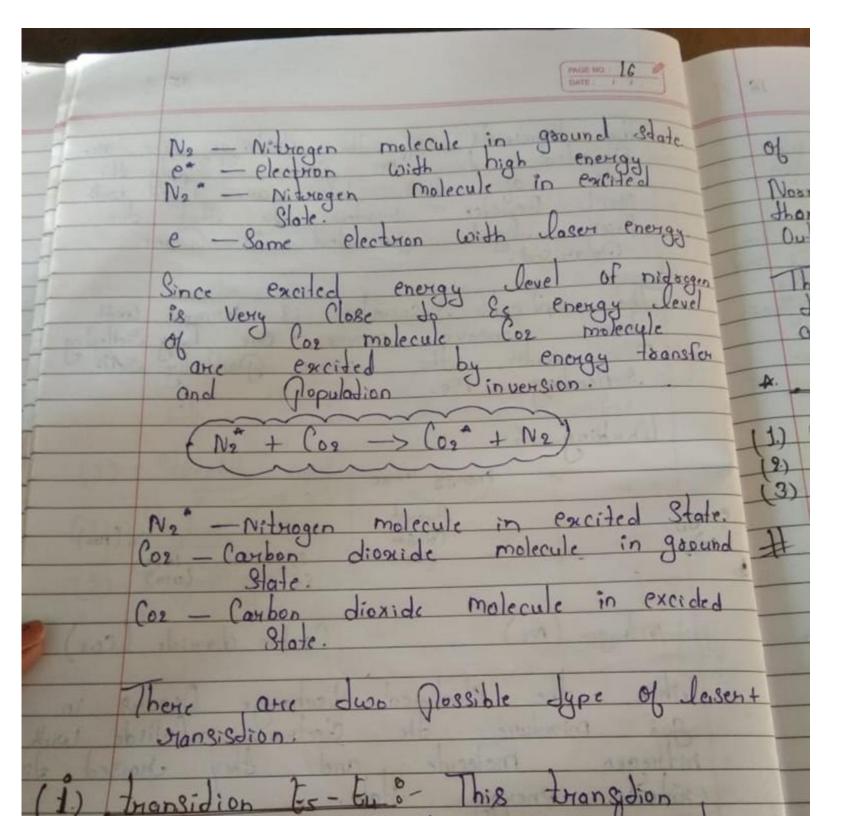




DATE I Purpose of the He along is do help achiving the in atom. Appulation inversion nean J When an excided near atom pass from mela Stable Blate of 90.66ev an excided State of 13070 ev. the 00 emids a Thoton of wove length Arough 6328 A° Shis gas mixture and moving in the ends undill it Stimulated an excited dube atom and Causes it to emit neon Those with Simulated Tholon this Process is Condinue and When a been of Cohenent Fradiation becomes intence, a postion of its Scope, through the Partially gilver end the atom passes Spontaneously do neon clower energy level and finally somes a le les land despecialisme



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It undergoes TIR from Side walls and

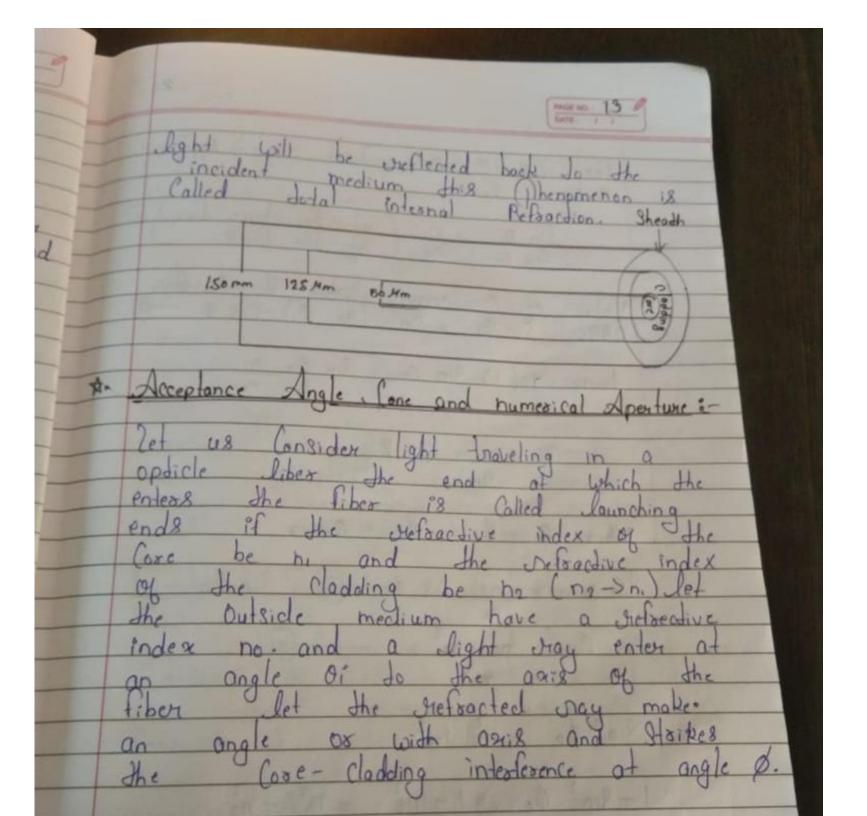
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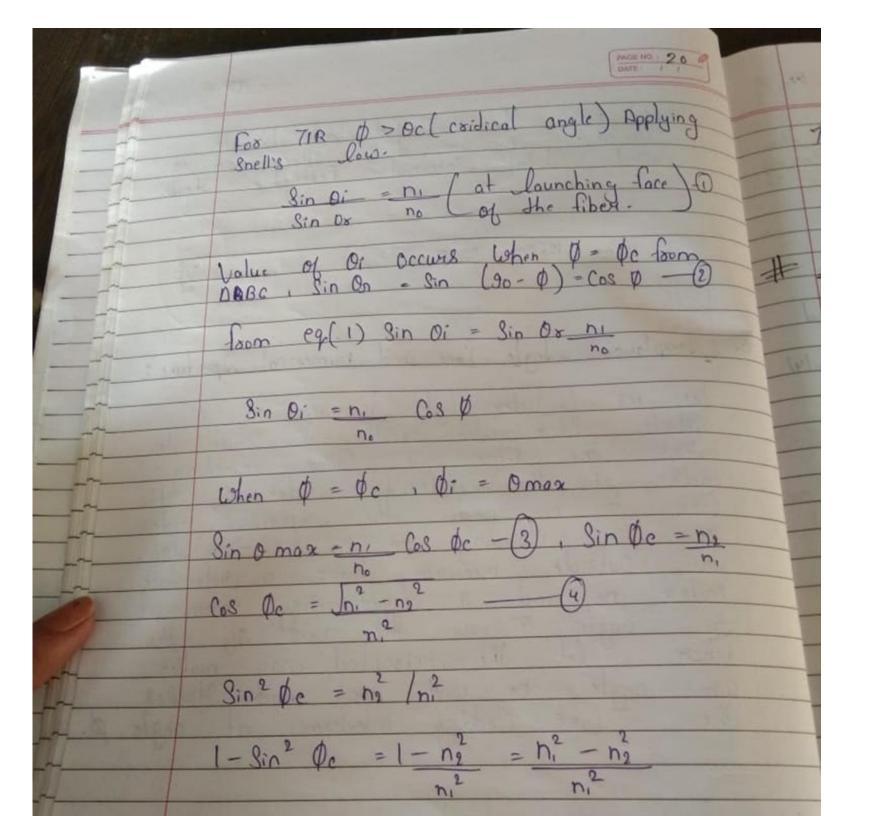
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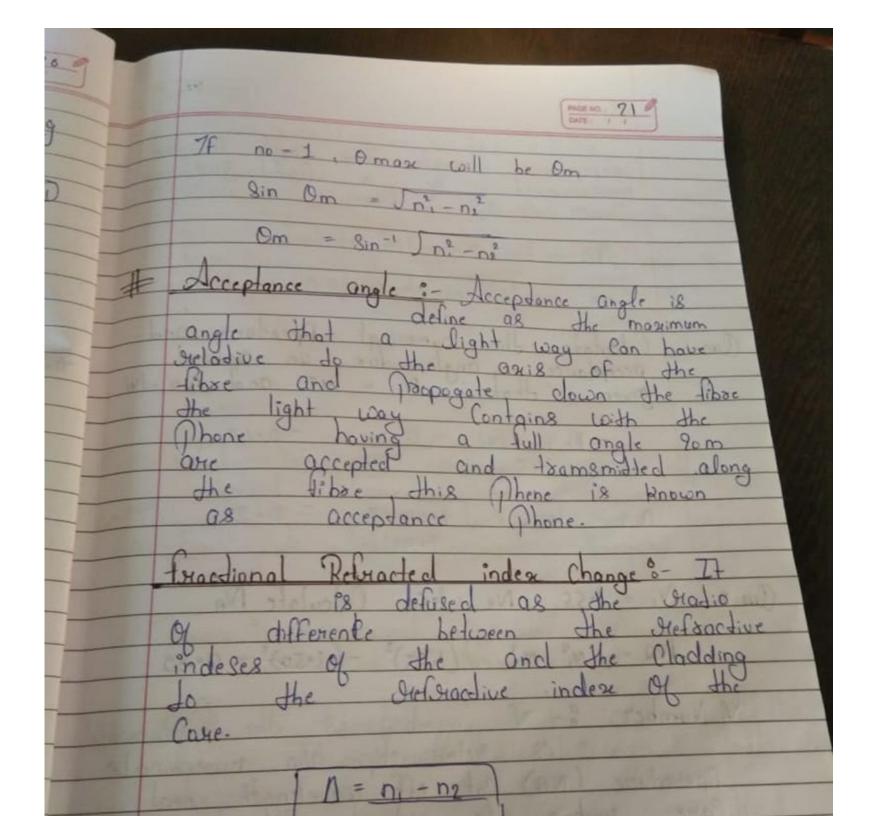
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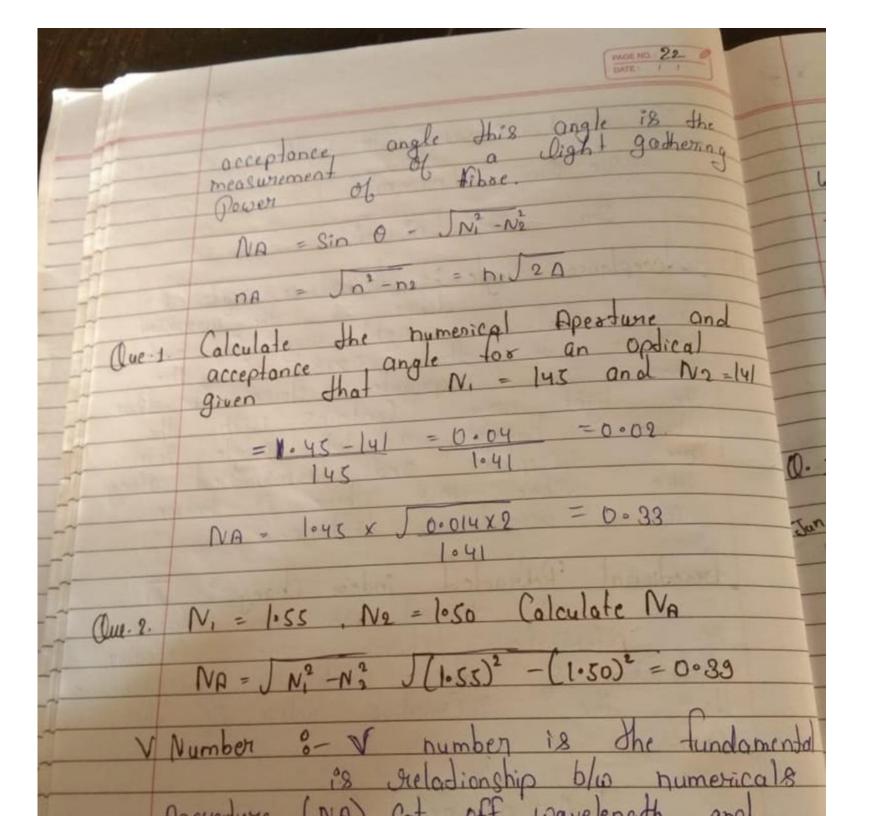
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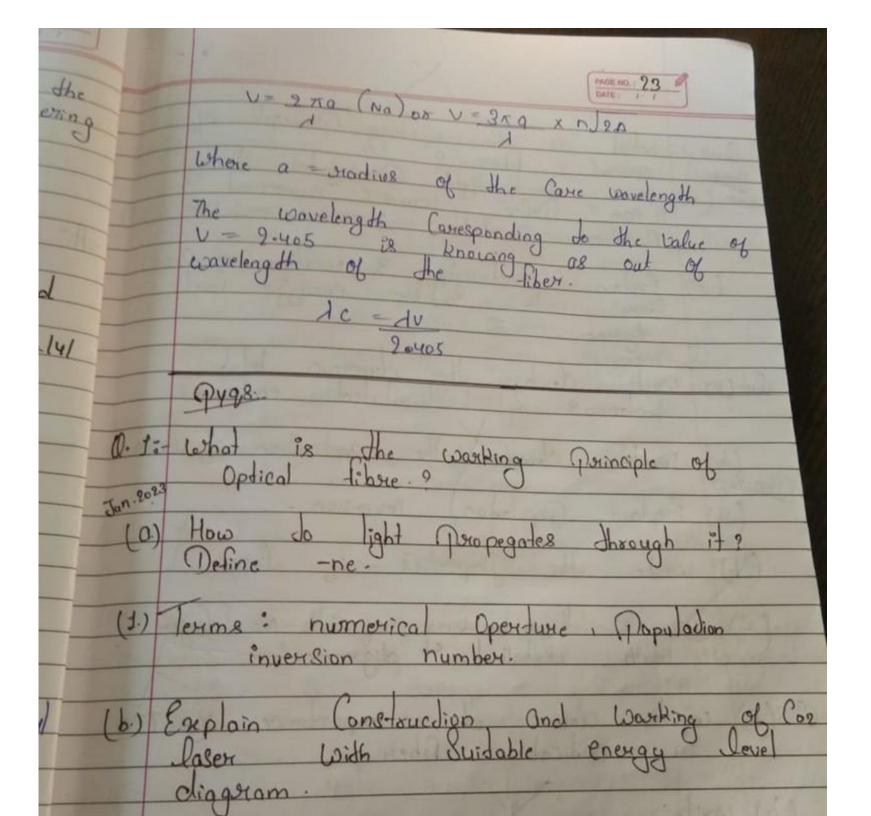
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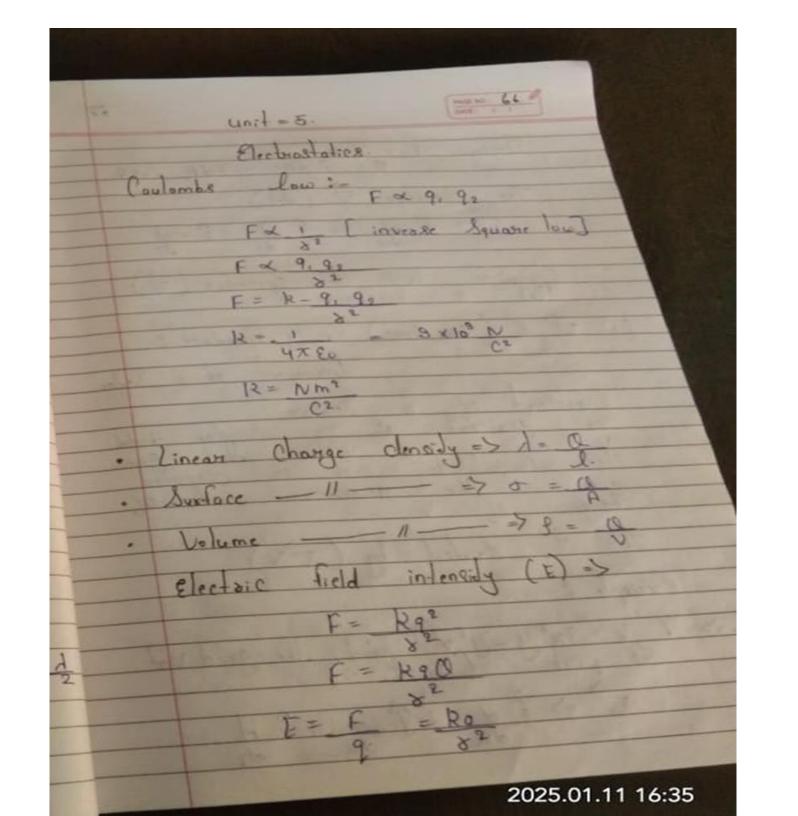


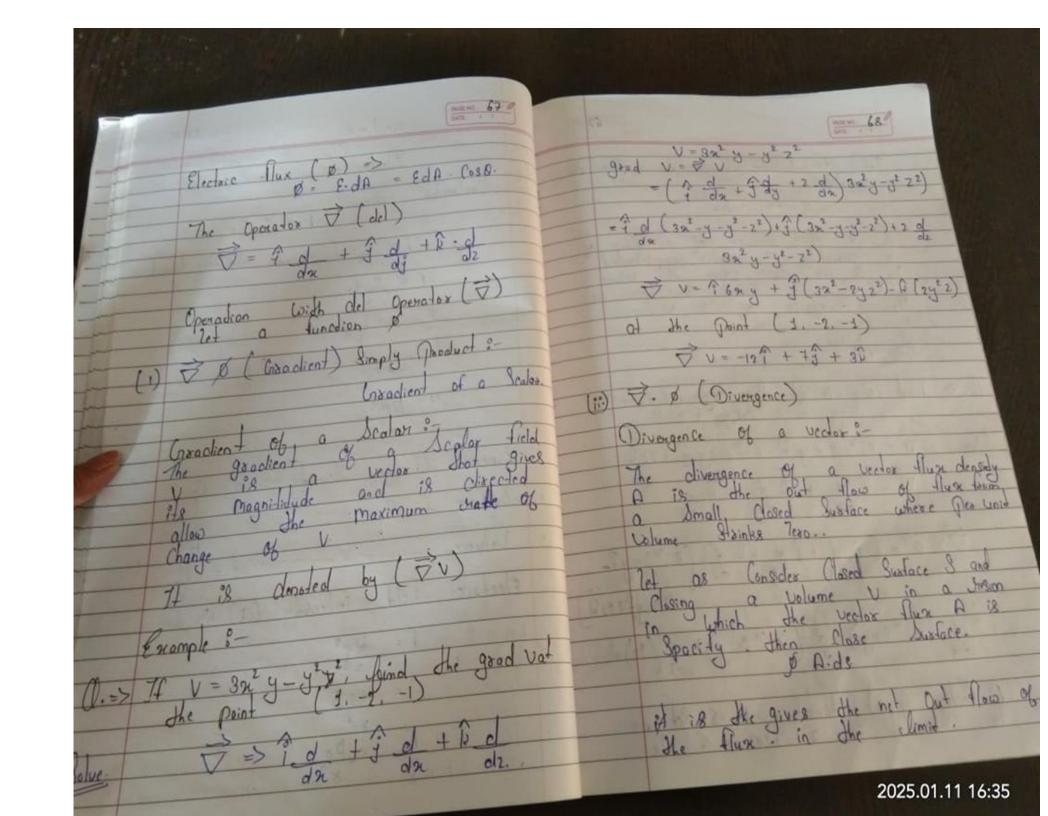


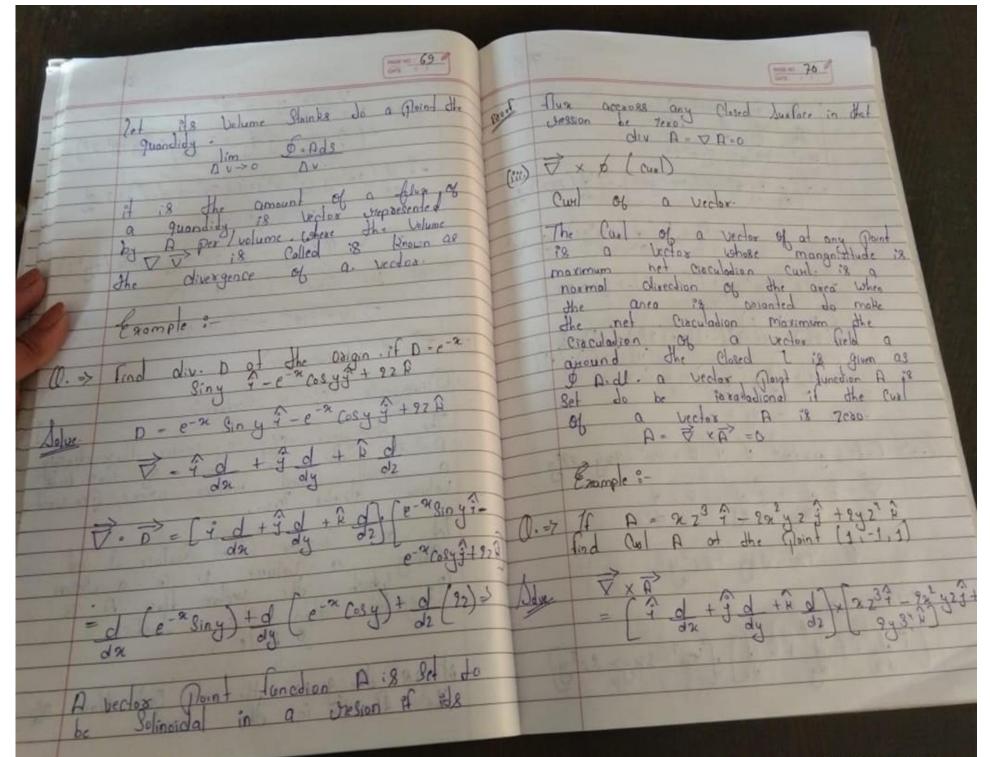


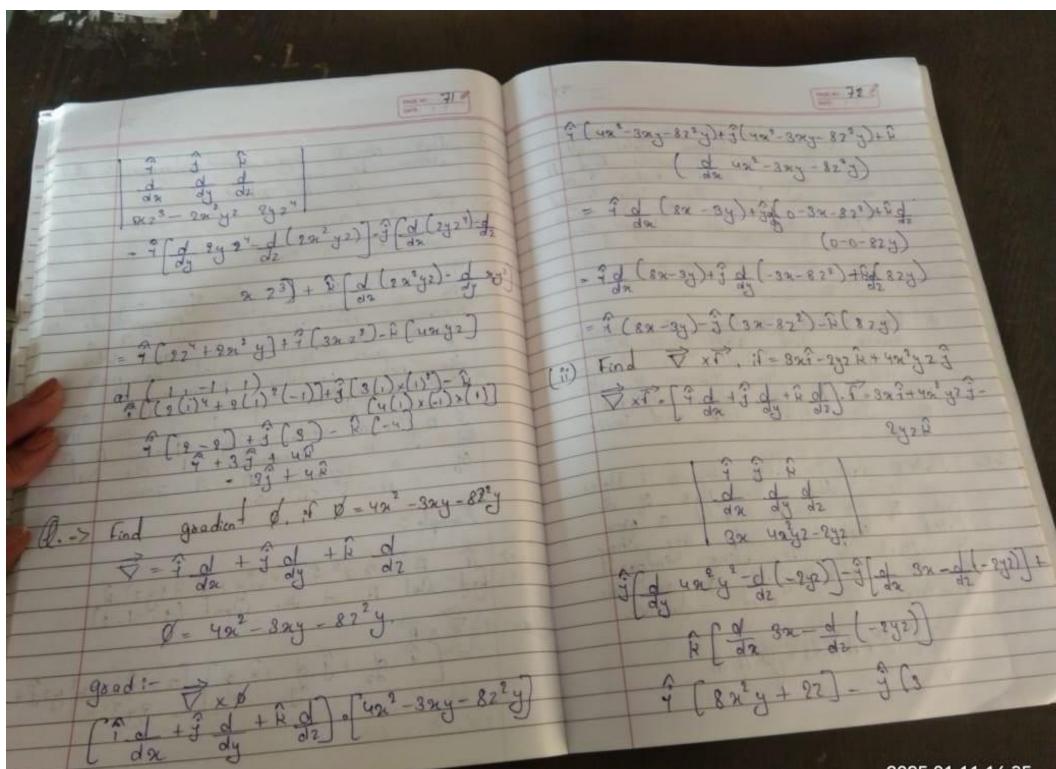


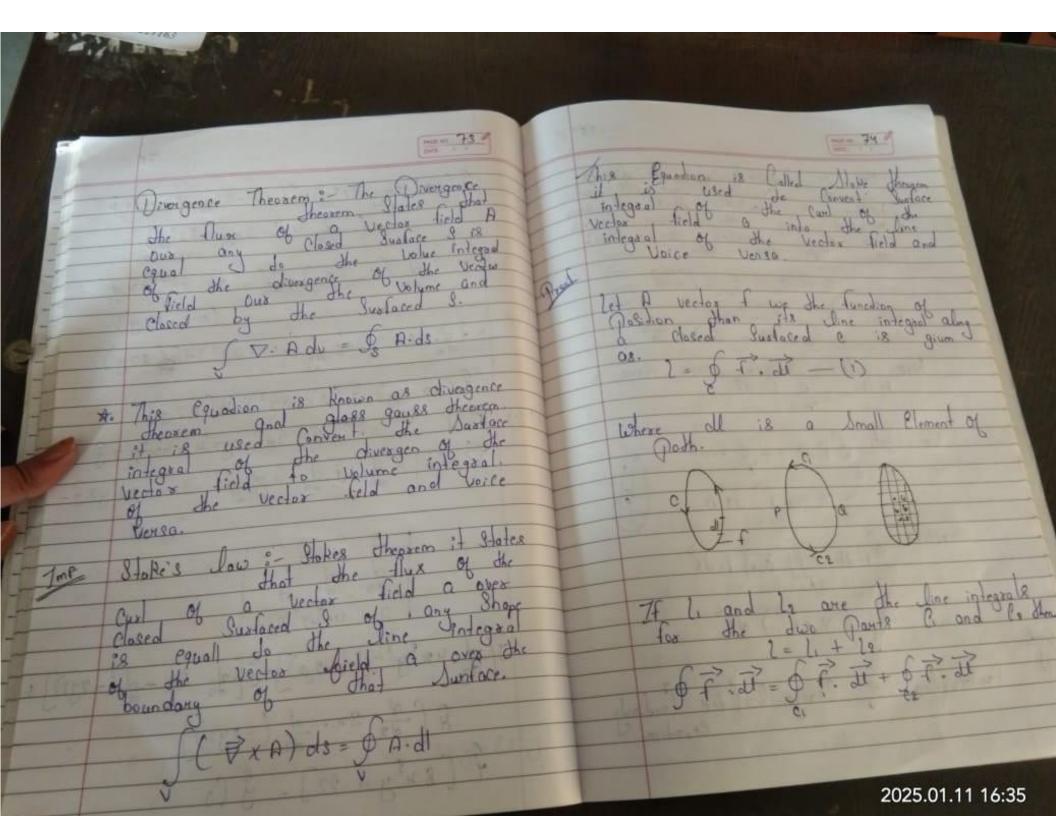
(Dec. 2023) Xa) Explain Dopulation inversion wide The Pappendies lasers. 884023 (C) Washing He- Ne losen with laballed diggram (1.(2) (a) casade cloups the Proportance of TIB in Operical. clown the application of Carcide Engineering and madicine alculate, NA and acceptance angle opdical. given do enforcidire the Care and Cladding are 1.45 indices Joys Despectively. Not. 9022 reladionship blu einstine (a) (1) sive the Cofficient. a.2:- (a) Explain the Constauction and Lookbing He- Ne laser. Opdical fibre Calculate Explain NO an with retinaction NA Cladding are 1.55 and Care Grespe Cdive y. 050 and an 8- Disoperdies of laser light note

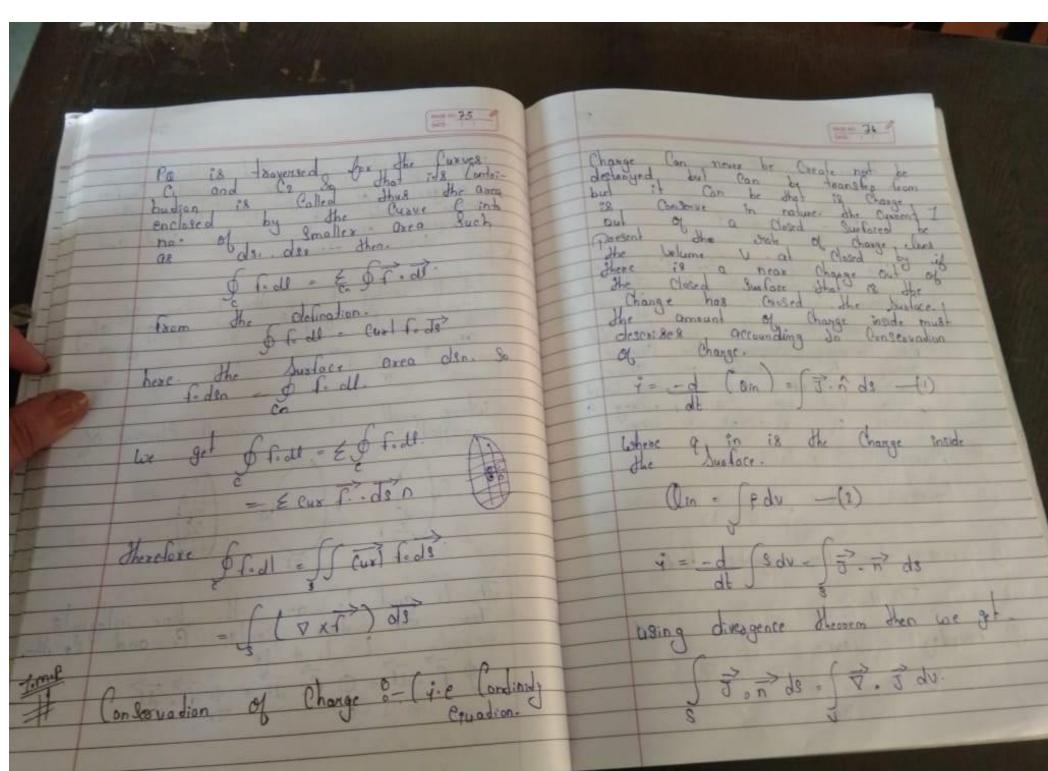












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